FOR REFERENCE

TOT U BE TAKEN FROM THIS ROOM

QUASI-STATIC DESIGN CONSIDERATION

OF MICROSTRIP LINES

by

Selçuk ÖZKANLI

B.S. in E.E., Boğaziçi University, 1983

Submitted to the Institute for Graduate Studies in Science and Engineering in partial fulfillment of the requirements for the degree of

Master of Science

in

Electrical Engineering



Boğaziçi University

QUASI-STATIC DESIGN CONSIDERATION OF MICROSTRIP LINES

APPROVED BY

Prof. Dr. Adnan ATAMAN _ (Thesis Supervisor)

18.19-

Prof. Dr. Bingül YAZGAN

Dog. Dr. Selim ŞEKER

DATE OF APPROVAL JANUARY 31, 1986

ACKNOWLEDGEMENTS

I would like to express my sincere gratitude to those who have helped me during the development of this study, especially to my thesis supervisor Prof. Dr. Adnan_ATAMAN for his kind interest and invaluable aid.

I am also indepted to Turkish Land Forces who gave me opportunity to get my entire graduate education in the Faculty of Engineering at Boğaziçi University.

196225

11:

QUASI-STATIC DESIGN CONSIDERATION OF MICROSTRIP LINES

ABSTRACT

Although microstrip lines have been extensively investigated by a large number of researchers, and their theory and design have been reported in many articles, there is no comprehensive description available at one place. In particular the design information is not readily available.

This study is basically intended for presenting a detailed account of these lines. It describes analysis and design of this transmission medium. The features discussed include guasi-static and fullwave analyses, detailed design considerations including CAD and measurement procedures.

Particularly, the results of six different approaches given for characteristic impedance and effective dielectric constant calculations are compared with each other and among them, equations giving the nearest values to the results of numerical methods and experiments are used to calculate the other microstrip characteristics.

MIKROŞERITLI HATLARIN SÖZDE-STATIK

YUNTEMLERLE TASARIMI

ÖZET

Mikroşeritli hatlar birçok araştırmacı tarafından oldukça geniş bir şekilde araştırılmış ve teorisi ile tasarımı birçok makalede sunulmuş olmasına rağmen, bu konuda etraflı bir kaynak elde mevcut değildir.

Bu çalışmanın temel olarak amacı mikroşeritli iletim hatlarının analiz ve tasarımını ayrıntılı bir şekilde ve bir bütün olarak sunmaktır . Üzerinde durulan konular sözdestatik ve tümdalga analizlerini, bilgisayar destekli tasarımı da kapsayan, tasarımda gözönünde bulundurulması gerekli bilgiler ile ölçme işlemlerini içerir.

Özel olarak tasarım sırasında, karakteristik empedans ve etken dielektrik katsayısının hesabı için verilmiş altı değişik yaklaşımın sonuçları birbirleriyle karşılaştırılmış ve bunlar arasında sayısal metodlar ile deneysel çalışmaların sonuçlarına en yakın değerleri veren eşitlikler, mikroşeritli iletim hatlarının diğer karakteristiklerinin hesabında kullanılmıştır.

TABLE OF CONTENTS

ala ang kanala na ka Na kanala na kanal <u>a</u> k	Page
ACKNOWLEDGEMENTS	iii
ABSTRACT	iv
ÖZET	V
LIST OF FIGURES	×
LIST OF TABLES	xii
LIST OF SYMBOLS	xiv
CHAPTER I. INTRODUCTION	1
CHAPTER II. BASIC CONCEPTS	3
2.1. Planar Transmission Structure	3
2.2. Definition and Field Configuration	7
2.3. Comparison of Microstrip with	
Conventional Transmission Media	11
CHAPTER III. METHODS OF MICROSTRIP ANALYSIS	12
3.1. Quasi-Static Analyses of Microstrip	14
3.1.1. Modified Conformal Transformation	
Method	15
3.1.2. Finite Difference Method	23
3.1.3. Variational Method in Fourier	
Transform Domain	23

	3.2. Microstrip Dispersion Models	24
	S.Z. MICIOSCIIP Dispersion Models	
• • •	3.2.1. Dielectric-loaded Ridged	
		25
	Waveguide Model	
	3.2.2. Planar Waveguide Model	28
		2.0
	3.3. Fullwave Analysis	30
	NTODOGEDID DECION CONCIDEDAMIONO	31
HAPTER IV.	MICROSTRIP DESIGN CONSIDERATIONS	31
	4.1. Microstrip Losses	31
		-
	4.1.1. Conductor Loss	32
	4.1.2. Dielectric Loss	35
	4.1.2. DIELECTIC LOSS	55
	4.2. Power Handling Capability	37
	4.2.1. Average Power Handling Capability	37
		39
	4.2.2. Feak Fower handling capability	59
andra Mariana Mariana Mariana	4.3. Effect of Tolerances	42
 A second s	4.4. Effect of Dielectric Anisotropy	42
	4.5. Design Equations	42
	4.5.1. Characteristic Impedance and	
	Effective Dielectric Constant	43
	a. Line-Capacitance Computation	
	Method	44
		• •
e de la composición d La composición de la c	b. Modification to the Method	
		46
	Given in a	40
an a		

c. Modification to the Method Give	an
in b	47
d. Generalization of Schneider's	
Standard Equation Obtained by	
Exact Conformal Mapping	49
e. Modification to Schneider's	
Effective Dielectric Constant	
Equation given in d	54
f. New Equations	58
	63
4.5.2. Effect of Enclosure	63
4.5.3. Effect of Dispersion	69
4.5.4. Losses	71
4.5.5. Quality Factor	73
CHAPTER V. MICROSTRIP MEASUREMENTS	, 76
5.1. Substrate Dielectric Constant	77
5.2. Characteristic Impedance	80
5.3. Phase Velocity or Effective Dielectric	
Constant	81
5.4. Attenuation Constant	82
CHAPTER VI. COMPUTER AIDED DESIGN OF MICROSTRIP LINES	84
6.1. Program for Microstrip Design	84
6.2. Comparison by a Computer Program Using	
Graphs	84

CHAPTER VII. CONCLUSION		100
APPENDIX A. DATA ON COMMONL	Y USED SUBSTRATES	FOR
MICROSTRIP		104
APPENDIX B. DESIGN OF MICRO	STRIP LINES BY USI	ING THETA
FUNCTIONS		106
BIBLIOGRAPHY		108

REFERENCES NOT CITED

LIST OF FIGURES

Pa

	. .		
FIGURE	2.1	Planar Transmission Lines Used in MIC's	4
FIGURE	2.2	Various Transmission Lines Derived from	
		Microstrip	б
FIGURE	2.3	Stripline Configuration	7
FIGURE	2.4	Cross-section of a Microstrip	7
FIGURE	2.5	Conceptual Evolution of a Microstrip from a	1
		Two-wire Line	8
FIGURE	3.1	Various Methods of Microstrip Analysis	ີ 13
FIGURE	3.2	Conformal Transformation and Evaluation of	*.
		Effective Dielectric Constant (from[3])	18
FIGURE	3.3	Characteristic Impedance and Effective	
		Dielectric Constant of Microstrip Lines	
		Calculated Using Wheeler's Method	22
FIGURE	3.4	Ridged Waveguide Model for Microstrip Line	26
FIGURE	3.5	Planar Waveguide Model for Microstrip Line	28

- FIGURE 4.1 Recession of Conducting Walls of Microstrip for Loss Calculation Using "Incremental Inductance Rule" 33
- FIGURE 4.2 Microstripline with Associated Capacitances 45

53

77

- FIGURE 4.3 Square Root of the Effective Dielectric Constant for the Microstrip
- FIGURE 4.4 Conductor and Dielectric Losses as Functions of Frequency for Microstrip Lines on Various Substrates 73
- FIGURE 4.5 Variation of Q-factors with Frequency for Quarterwave Microstrip Resonators 75
- FIGURE 5.1(a) Metallized Subtrate as a Parallel Plate Resonator
- FIGURE 5.1(b) Resonance Frequencies for Various Models of a Metallized Substrate Resonator 78

FIGURE 5.2 Test Configuration for Resonance Measurements79

LIST OF TABLES

			Page
TABLE	2.1	Comparison of Various MIC Lines	5
TABLE	2.2	Comparison of Conventional Transmission Media	1 Ìl
TABLE	4.1	Comparison of Average Power Handling Capabili	lty
		(APHC) for Various Substrates	39
TABLE	4.2	Comparison of Calculated and Measured Charac-	-
		teristic Impedances for Methods a, b, and c	1
		$(\varepsilon_r = 4.7)$	50
TABLE	4.3	Comparison of Characteristic Impedances	· 2 ·
		Calculated from Methods a, b and c with	
		Numerical Methods (6)	-51
TABLE	4.4	Comparison of Calculated and Measured	
		Characteristic Impedances for Methods d and e	:
		$(\varepsilon_{r} = 4.7)$	56
TABLE	4.5	Comparison of Characteristic Impedances	
		Calculated from Methods d and e with Charac-	
	· , 	teristic Impedance Obtained by Numerical	
		Methods (6)	57

Xii

- TABLE 4.6 Comparison of Characteristic Impedance for ZeroThickness Microstrip Calculated by DifferentMethods64
- TABLE 4.7 Comparison of Effective Dielectric Constant for Zero Thickness Microstrip Calculated by Different Methods
- TABLE 4.8 Comparison of Calculated and Measured Characteristic Impedances for Method f with Zero Thickness and Including Strip Thickness ($f_r = 4.7$) 66
- TABLE 4.9 Comparison of Characteristic Impedances Calculated by New Equations (Method f) with Numerical Methods (6) 67
- TABLE 4.10 Comparison of Effective Dielectric Constant for Microstrip Including Strip Thickness Calculated by Different Methods 68

LIST OF SYMBOLS

APHC	•	Average power handling capability
C		Capacitance per unit length
C _a	•	Capacitance with substrate dielectric replaced by air
C	:	Velocity of electromagnetic waves in free space
Ε	•	Electric field
E _x , E _y , E _z	a 	Components of Electric field E
FTD	•	Fourier transform domain
H	•	Magnetic field
^H _x , ^H _y , ^H _z	:	Components of magnetic field H
h	:	Height of the substrate
K(m), K'(m)	:	Complete elliptic function and its complement
L	•	Inductance per unit length
L _i	:	Incremental inductance

Longitudinal section electric LSE : Natural logarithm (to the base e) ln : loq Common logarithm (to the base 10) : Microwave integrated circuit MIC : Peak power handling capability PPHC : : Charge Q Quality factor Q_c, Q_d, Q_r Various quality factors : Q_T, Q_o Filling fraction : q Charge density Surface resistivity R : Temperatures T, T_{max}, T_{amb} : Time domain reflectometer/reflectometry : TDR Transverse electromagnetic TEM : Loss tangent : tanδ Effective loss tangent (tand)eff : Voltage . V : Voltage standing wave ratio VSWR

xv

v _p :	Phase velocity
₩ (*	Strip width for microstrip
^w eff :	Effective strip width for microstrip
^w eff ^(f) :	Frequency dependent w _{eff}
z _o :	Impedance per unit length for microstrip
z _o a:	Characteristic impedance with substrate replaced by air
α \$	Attenuation constant
^α c :	α because of conductor loss
^α d :	$_{\alpha}$ because of dielectric loss
β	Phase constant
δ	Skin depth
ε	Permittivity
ε ₀ :	ϵ for free space
er :	Relative permittivity
[¢] eff :	Effective dielectric constant
<pre> ^εeff^(f) : </pre>	Frequency dependent c eff
ε', ε"	Real and imaginary parts of ε

xvi

: Free space impedance (=1201 ohms)

Wavelength

:

.

•

:

: .

:.

:

:

:.

:

:

:

ζ

λ

λo

 λ_{m}^{\prime}

μ

μö

П

ρ

 $\overline{\mathbf{G}}$

 $\widetilde{\mathfrak{feff}}$

Ω

ŵ

Free space λ

 λ for microstrip

Permeability

Free space permeability

A constant (3,1416)

Charge density

Conductivity

Effective conductivity

Ohm

Angular frequency (=21f)

Tilde indicates Fourier transform

I. INTRODUCTION

The microstrip line, consisting of a strip conductor on a dielectric substrate backed by a ground plane, has experienced increased popularity in recent years in computer and microwave integrated circuit design with the availability of new low-loss substrate materials and the rapid development of semiconductor devices in the microwave frequency regions. Its simple structure, light weight and ruggedness make it an excellent substitute for coaxial and conventional waveguides in many applications.

Microstrip lines which are used as a circuit element in microwave integrated circuits (MICs) are called "thin microstrips" in which the ratio of strip conductor thickness, t, to substrate thickness, h, lies between 0.01 and 0.05, whereas "thick microstrips" (0.05 < t/h < 0.2) are used as a transmission line for high-speed computers. In this study, there is no special aim to describe one of these versions, especially.

The text is divided into seven chapters. Chapter 2 gives a brief description of planar transmission structures

and field configuration of microstrip. A comparison of microstrip with conventional transmission media is also given in this chapter.

Chapter 3 is concerned with the methods of microstrip analysis.

Chapter 4 presents the detailed design considerations including design equations, effects of tolerances and enclosures, losses, etc. and ensures the direct design of microstrip lines without going into details of analysis. Six different sets of equations are given here, enabling the reader to make a comparison.

Chapter 5 outlines the methods for the measurement of microstrip characteristics and for subtrate dielectric constant, briefly.

In chapter 6, it is desired to provide a computer aided design of microstrip. Also, a computer program ensuring to make a comparison of characteristic impedances or effective dielectric constants obtained from different approaches, with each other for desired t/h and w/h ratios by using a special plot algorithm is presented.

II. BASIC CONCEPTS

2.1 PLANAR TRANSMISSION STRUCTURES

A transmission structure should be "planar" in configuration to be used as a circuit element in microwave integrated circuits (MICs). A planar configuration implies that the characteristics of the element can be determined by the dimensions in a single plane. For example, the substrate thickness or the strip conductor width of the microstrip can be adjusted to control its characteristic impedance. When the impedance is controlled by a dimension in a single plane, the fabrication of the circuit can be easily carried out by the photo-etching of thin films and photolithographic techniques. Use of these techniques at microwave frequencies has led to the development of MIC's.

There are several transmission structures having planar configuration. The most common of these are :

- (i) Microstrip
- (ii) Slotline
- (iii) Coplanar strips (CPS)
- (iv) Coplanar waveguide (CPW)

The cross-sectional views of these lines are shown in Figure 2.1. Also, a comparison of performance characteristics is given in Table 2.1. Among these transmission structures, microstrip line is the most popular, mainly due to the fact that the mode of propagation on microstrip is almost TEM. This allows an easy approximate analysis.

a MICROSTRIP	b _SLOTLINE
c.COPLANAR WAVEGUIDE	d.COPLANAR STRIPS

Figure 2.1. Planar Transmission Lines Used in MICs

	and the second second	1		
CHARECTERISTIC	HICROSTRIP	SLOTLINE	COPL. WAVEQUIDE	COPL. STRIPS
POWER HANDL. CAP.	HJGH	LOW	NEDIUM	MEDIUM
RADIATION LOSS	LOW	HIGH	MEDIUM	NEDIUM
UNLO ADED Q	HJCH	LOW	. NEDIUM	Low
DISPERSION	SMALL	LARGE	MEDIUAL	MEDIUM
NOUNTING OF COMP .:				
IN SHUNT CONF.	DIFF.	EASY	EASY	EASY
IN SERIES CONF.	EASY	DIPF.	EASY	EASY
ENCLOSURE DIN.	SMALL	LARGE	LANGE	LARGE

TABLE 2.1. Comparison of Various MIC Lines

There are several variations of microstrip configuration that have also been suggested for use in MICs. These include inverted microstrip, suspended microstrip, microstrip with overlay, strip dielectric waveguide and inverted strip dielectric waveguide. Cross-sectional views of these structures are given in Figure 2.2.

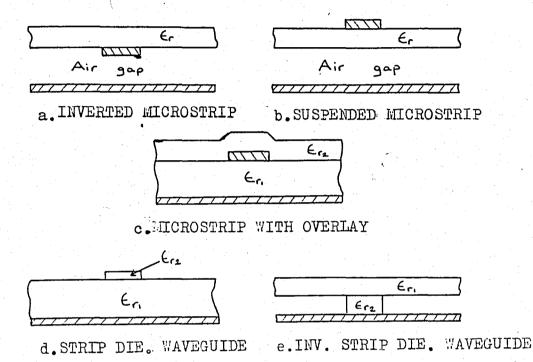


Figure 2.2. Various Transmission Lines Derived from Microstrip

Another very commonly used transmission line that resembles microstrip line is the stripline shown in Figure 2.3. This is also called triplate line. Most of the basic circuit design information available for stripline is also applicable to microstrip line.

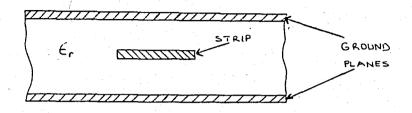


Figure 2.3. Stripline Configuration

2.2. DEFINITION AND FIELD CONFIGURATION

A cross-section of a microstrip is shown in Figure 2.4. It consists of a dielectric substrate with a metal ground-plane on one side and a metal strip on the other.

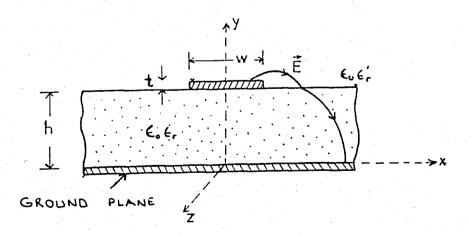


Figure 2.4. Cross-section of a Microstrip

The electrical properties of microstrip will depend on the geometry : strip width w, strip thickness t, and substrate thickness (height) h : and on the dielectric and magnetic properties of the substrate and the medium above, which are considered to have infinite entent. The medium above the substrate is usually air which dielectric constant $\varepsilon_0 \varepsilon_r'$ can be assumed to be equal to that of free space $\varepsilon_r' = 1$ and $\varepsilon_0 = 8.8542 \times 10^{-12}$ F/m (in the SI system of units). The relative dielectric constant of the substrate

Conceptually, it can be said that microstrip is a two-conductor transmission line which is evolved from a two-wire line as shown in Figure 2.5.

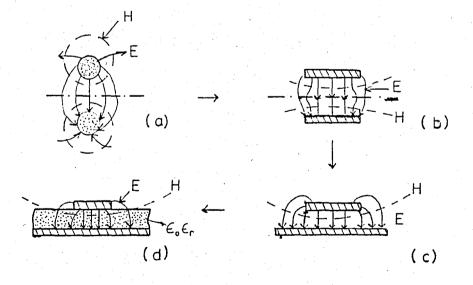


Figure 2.5. Conceptual Evolution of a Microstrip from a Two-wire Line

Transformation from (a) to (b) is essentially a change in the shape of the conductors, whereas that from (b) to (c) involves placing a conducting sheet at the plane of symmetry. The final configuration (d) is obtained by inserting a thin dielectric slab between the two conductors. As a consequence of the last step, the dielectric medium of the transmission line becomes inhomogenous.

Microstrip lines differ considerably from other transmission lines. For example, comparing it with a stripline one observes that the microstrip structure is open on the top. This open configuration makes microstrip very convenient for use in MICs where discrete lumped devices (active or passive) are to be mounted in the circuit. Also, a slight adjustment or tuning can possibly be incorporated after the circuit has been fabricated. However, along with these advantages, the open structure of microstrip brings in some complications in microstrip analysis and design. This is due to the fact that the presence of dielectricair interface modifies the mode of propagation in microstrip to a non-TEM hybrid mode.

Simple arguments based on the known guasi-static field distribution of the microstrip and Maxwell's equations can be put forward to show that microstrip structure cannot support a pure TEM wave. Continuity of the tangential component of the electric field along the dielectric-air

interface (look at Figure 2.4) gives

$$E_{\mathbf{x}} \begin{vmatrix} \mathbf{z} & \mathbf{z} \\ \mathbf{z} & \mathbf{z} \end{vmatrix}$$
(2.1)

щυ

where subscripts a and d refer to the air and the dielectric side of the interface, respectively. Using Maxwell's equation, we may thus write

$$\varepsilon_{r}(\vec{\nabla} \times \vec{H})_{x} = (\vec{\nabla} \times \vec{H})_{x}$$
(2.2)

Expanding Equation (2.2) and using the continuity of normal component of magnetic field, we obtain

$$(\varepsilon_r^{-1}) \frac{\partial H_y}{\partial z} = \varepsilon_r \frac{\partial H_z}{\partial y} | - \frac{\partial H_z}{\partial y} |$$
 (2.3)

As ε_r is not equal to unity and $H_y \neq 0$, Equation (2.3) implies that the expression on its right hand side should be a nonzero quantity, which can be true only if H_z is non-zero. Thus we note that for Maxwell's equations to hold good for the configuration of Figure 2.4, the longitudinal component of H should exist.

Similar arguments can be advanced to show that E_z , the longitudinal component of electric field, is also a non-zero quantity. It may be pointed out that it is only the fringing components E_x and H_x at the air-dielectric interface that lead to the non-TEM nature of the microstrip mode. Since these fringing field components are much smaller than the main field (within the substrate below the strip), the departure from the TEM behavior should be small.

2.3. COMPARISON OF MICROSTRIP WITH CONVENTIONAL TRANSMISSION MEDIA

Microstrip technology is quite mature and offers a superior blend of performance characteristics to the designer of microwave integrated circuits. A comparison of performance characteristics of conventional transmission media is given in Table 2.2.

TABLE 2.2. Comparison of Conventional Trasmission Media

CHARECTERISTI C	MICROSTRIP	STRIPLINE	COAXIAL	WAVEQUIDE
LINE LOSSES	HICH	HIGH	NEDLUN	Low
NHLOADED Q	LOW	LOW	MEDIUN	HIGH
POWER CAP.	LOW	LOW	MEDIUM	HIGH
ISOLATION BET. NEIGHBORING CIR.	POOR	FAIR	Y. 6000	V.600D
BANDWITH	LARGE	LARGE	LARGE	SHALL
MENEATURIZATION	EXCEL_	V. COOP	POOR	POOR
VOLUME & WELGHT	SMALL	MEDIUN	LARGE	LARGE
REALL. OF PAS. CIR.	VLEASY	V.EASY	EASY	EASY
INTEG. WITH CHIP DE.	V.GOOD	FAIR	POOR	POOR
INTEG. WITH FERRITES	6000	G0 00	FOOR	GODD
INTEG. WITH LURP. EL.	V.GOOD	V. GOOD	G0 00	FOOR

III. METHODS OF MICROSTRIP ANALYSIS

There are various methods of microstrip analysis. These methods can be divided into three groups as shown in Figure 3.1.

In the first group which comprises quasi-static methods, the nature of the mode of propagation is considered to be pure TEM, and microstrip characteristics are calculated from the electrostatic capacitance of the structure.

In the second group, called dispersion models, the deviation from the TEM nature is accounted for quasi-empirically. Some parameters of the model are determined such that the final expression agrees with the known experimental (or exact theoretical) dispersion behavior of the microstrip.

The methods in the third group take into account the hybrid nature of mode of propagation. Fullwave analysis is carried out for determining the propagation constant instead of the capacitance evaluated in quasi-static analysis.

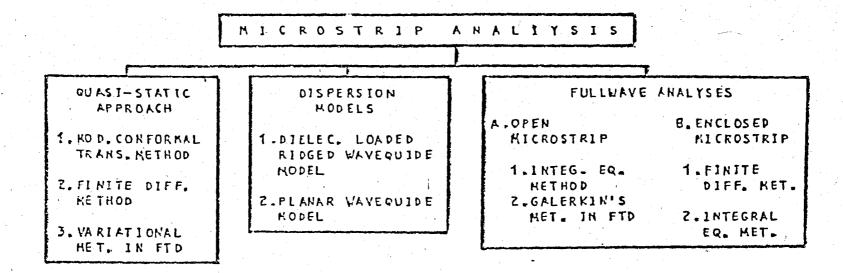


Figure 3.1 : Various Methods of Microstrip Analysis

3.1. QUASI-STATIC ANALYSES OF MICROSTRIP

In quasi-static analyses, the mode of wave propagation in microstrip is assumed to be pure TEM. Transmission characteristics are then calculated from the values of two capacitances :

> (i) C_a: Capacitance for a unit length of the microstrip configuration with the dielectric substrate replaced by air

(ii) C : Capacitance for a unit length of the microstrip with the dielectric substrate present.

Values of characteristic impedance ${\tt Z}_{0}$ and the phase constant β can be written in terms of these capacitances as follows :

$$Z_{o} = Z_{o}^{a} (C_{a}/C)^{1/2}$$
 (3.1)

and

 $\beta = \beta_0 (C/C_a)^{1/2}$ (3.2)

where $Z_0^a = 1/(c.C_a)$ and $\beta_0 = \omega/c$; c being the velocity of electromagnetic waves in free space. There are various methods available for calculation of electrostatic capacitances C_a and C. Three of these are listed in Figure 3.1 and only the first one will be discussed in detail in the following sub-section. 3.1.1. MODIFIED CONFORMAL TRANSFORMATION METHOD

An exact conformal transformation for the impedance of a zero thickness, homogeneous dielectric microstrip has been given by Schneider at 1969⁽¹⁾.

The transformation from the microstrip (Z_1 -plane) to a parallel plate capacitor (Z-plane) is expressed in terms of the derivative of the logarithm of the theta function Q_4 and its parameter $\kappa = K'/K$ as follows :

$$Z_{1} = Z_{1}(Z) = -\frac{2hK}{\Pi} \frac{\partial}{\partial Z} \ln \left[Q_{4}(Z, \kappa)\right]$$
(3.3)

where K = K(m) and K' = K'(m) are complete elliptic integrals of first kind with modulus m.

The characteristic impedance Z_0^{a} of the microstrip of width w and height h (and t = 0) is obtained by solving the following equations :

$$\frac{w}{h} = \frac{2}{\Pi} \frac{\partial}{\partial s} \ln \left[\Omega_4(s, \kappa) \right]$$
(3.4)

$$dn^2(2K_{\$}) = E/K$$
 (3.5)

$$Z_{o}^{a} = 1/2(\mu_{o}/\varepsilon_{o})^{1/2} K'/K$$
(3.6)

where μ_0 and ϵ_0 are the free space permeability and permittivity respectively, and Z_0^a is the characteristic impedance of microstrip with dielectric substrate replaced by air. E = E(m) is the complete elliptic integral of second kind and dn is the Jacobian elliptic function. The derivative of the logarithm of theta function is given by the following (rapidly converging) series expansion

 $\frac{\partial}{\partial \S} \ln \left[Q_4(\S,\kappa) \right] = 4 \Pi \sum_{n=1}^{\infty} \frac{\sin(2n\pi \S)}{\exp(n\pi \kappa) - \exp(-n\pi \kappa)} (3.7)$

Equations from (3.4) to (3.6) can be used for the design of microstrip lines. The exact computation for one intermediate case by means of the series expansion for the derivative of the logarithm of the theta function is treated in APPENDIX B step by step.

The practical solution to this set of equations must be done with the help of a computer or with numerical tables. Because of this limitation the above method is not used very frequently.

The most widely used technique for microstrip analysis was introduced by Wheeler (2,3) in 1964-65. The method involves use of a conformal transformation for evaluation of C_a and introduces a concept of effective dielectric constant for evaluation of C. The conformal transformation selected is such that the resulting expressions are explicit

and can be written in terms of simple functions. The transformation used for the wide strip (w/h>2) is

$$Z_1 = JII + d \tanh(Z/2) - Z$$
 (3.8)

The variable Z_1 refers to the microstrip plane (see Figure 3.2) and Z is the plane where in the microstrip configuration transforms into a parallel plate capacitor configuration. The parameter d is approximately equal to g' of Figure 3.2 (b). The dielectric-air boundary of the microstrip substrate is transformed into an ellipticallooking curve ba' as shown in Figure 3.2(b). For evaluating the capacitance C, it is necessary to introduce approximations to modify the dielectric-air boundary. The curved dielectric-air boundary of Figure 3.2(b) is approximated by a rectangular boundary as shown in Figure 3.2(c). The area (Π S') over the curve is written in terms of a "parallel area" Π S" and a "series area" Π (S'-S"). These series and parallel areas can be written in terms of an equivalent parallel area s given by (Figure 3.2(d))

$$S = S'' + (S' - S'') / \varepsilon_{\gamma}$$
 (3.9)

The effective filling factor can then be written as

$$q = (q^{i} - a^{i} + s)/q^{i}$$

(3.10)

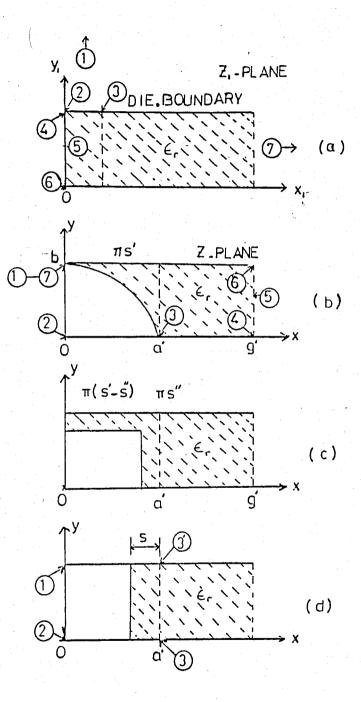


Figure 3.2. Conformal Transformation and Evaluation of Effective Dielectric Constant (from[3])

The effective dielectric constant is related to effective filling factor as

$$\varepsilon_{\text{eff}} = (1-q) + q\varepsilon_r \tag{3.11}$$

Different expressions for ε_{eff} are derived for wide microstrip (w/h > 2) and for narrow microstrip (w/h < 2) because of the different approximations used in two cases. For wide strips (4)

$$q = 1 - \frac{1}{d} \ln \frac{d+c}{d-c} + \frac{0.732}{d\varepsilon_{r}} \left[\ln \frac{d+c}{d-c} - \frac{1}{d-c} \right]$$

-Cosh⁻¹ (0.358d + 0.595) + $\frac{\varepsilon_{r}^{-1}}{d\varepsilon_{r}} \left[0.386 - \frac{1}{2(d-1)} \right]$
(3.12)

where $d = 1 + \sqrt{1 + c^2}$, and c is found implicitly from

$$\frac{\Pi}{2} \frac{W}{h} = c - \operatorname{Sinh}^{-1} c \qquad (3.13)$$

and for narrow strips

$$\varepsilon_{\text{eff}} = \frac{\varepsilon_{r}+1}{2} + \frac{\varepsilon_{r}-1}{2} \qquad \frac{\ln \frac{\pi}{2} + \frac{1}{2} \ln \frac{4}{\pi}}{\ln \frac{\pi}{2}} \qquad (3.14)$$

$$\frac{\ln \frac{8h}{w}}{w}$$

Formulas for the impedance of microstrip lines can be derived from these results. It is an advantage of the transformation selected by Wheeler that the impedance formulas can be written explicitly both for analysis (Z_0 in terms of w/h and ε_r) and for synthesis (w/h in terms of Z_0 and ε_r). These relations are listed below. For wide strips (w/h < 2)

$$Z_{0} = \frac{377}{(\varepsilon_{r})^{1/2}} \left[\frac{w}{h} + 0.883 + \frac{\varepsilon_{r}^{+1}}{\pi} \left\{ \ln\left(\frac{w}{2h} + 0.94\right) + 1.451 \right\} + 0.165 \frac{\varepsilon_{r}^{-1}}{\varepsilon_{r}^{2}} \right]^{-1}$$
(3.15)

and for narrow strips (w/h < 2)

$$Z_{0} = \frac{377}{2\pi (\frac{\varepsilon_{r}+1}{2})^{1/2}} \left[\ln \left(\frac{8h}{w}\right) + \frac{1}{8} \left(\frac{w}{2h}\right)^{2} - \frac{1}{2} \frac{\varepsilon_{r}-1}{\varepsilon_{r}+1} + \frac{1}{2} \left(\frac{1}{2} + \frac{1}{2} + \frac{1}{2$$

Expressions giving strip width for a desired impedance may be written as :

For wide strips (w/h < 2)

$$\frac{w}{2h} \Pi = \frac{377\Pi}{2(\varepsilon_r)^{1/2} Z_o} - 1 - \ln \left\{ \frac{377\Pi}{(\varepsilon_r)^{1/2} Z_o} - 1 \right\}$$

$$+ \frac{\varepsilon_{r}^{-1}}{2\varepsilon_{r}} \left[\ln \left\{ \frac{377\Pi}{2(\varepsilon_{r})^{1/2} z_{o}} - 1 \right\} + 0.293 - \frac{0.517}{\varepsilon_{r}} \right] (3.17)$$

and for narrow strips (w/h $\langle 2 \rangle$

$$\frac{2h}{w} = \frac{1}{4} e^{h'} - \frac{1}{2} e^{-h'}$$
(3.18)

where

h' =
$$\left(\frac{\varepsilon_{r}+1}{2}\right)^{1/2} \frac{Z_{o}}{60} + \frac{\varepsilon_{r}-1}{\varepsilon_{r}+1} \left(0.226 + \frac{0.120}{\varepsilon_{r}}\right)$$

(3.19)

Values of the characteristic impedance and effective dielectric constant of microstrip, based on the method discussed above, may be obtained from Figure 3.3. In this figure the value of $\sqrt{\epsilon_{eff}}$ is plotted as a function of w/h for various values of the subtrate dielectric constant. ϵ_r . The variation of characteristic impedance for air microstrip (Z_0^a for $\epsilon_r = 1$) is also shown by the dotted curve. Impedance for any value of ϵ_r can be obtained by dividing Z_0^a by the corresponding value of $\sqrt{\epsilon_{eff}}$. It may be seen from Figure 3.3 that the impedance value decreases when the strip width to substrate height ratio (w/h) is increased because an increase in w (or decrease in h) increases the line capacitance.

It may be pointed out that in the modified conformal transformation method discussed in this section, the thickness of the microstrip conductor is ignored and the analysis is restricted to an open microstrip without any enclosure.

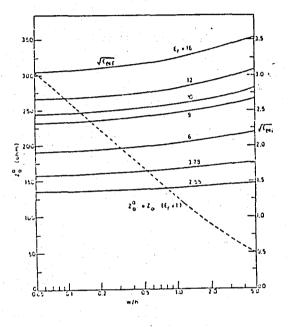


Figure 3.3. Characteristic Impedance and Effective Dielectric Constant of Microstrip Lines Calculated Using Wheeler's Method.

3.1.2 FINITE DIFFERENCE METHOD

Another method for quasi-static analysis of microstrip lines is based on the numerical solution of Laplace's equation in finite difference form⁽⁵⁾. The solution of Laplace's equation yields information about the potential distribution in the microstrip cross-section. Field distribution and the charge on the strip can be calculated therefrom.

Since this method is more suitable for enclosed microstrip, it is not explained in detail here.

3.1.3. VARIATIONAL METHOD IN FOURIER TRANSFORM DOMAIN

The search for microstrip analysis techniques which are computationally more efficient has led to the "Variational method in Fourier Transform Domain (FTD)". There are two significant features of this method ⁽⁶⁾. First, a variational method for calculating the capacitance C from the charge density ρ is used. This avoids the need for knowing the charge density distribution accurately. Secondly, the major portion of analysis is carried out in Fourier Transform Domain with the result that the integral equation for the potential is replaced by an ordinary product of an approximate $\tilde{\rho}$ and a factor \tilde{g} derived in FTD. (The superscript $\tilde{f}(\alpha) = \int_{-\infty}^{\infty} f(x) e^{j\alpha x} dx$).

Results obtained by this method agree well with those of the modified conformal transformation method discussed earlier.

This method can also be used to take into account the effect of finite strip thickness and enclosure. It can be easily extended for microstrip on composite substrates or where a dielectric overlay exists over the microstrip (7).

3.2. MICROSTRIP DISPERSION MODELS

The quasi-static methods of microstrip analysis peresented here do not take into account the non-TEM nature of the microstrip mode. The non-TEM behavior causes the effective dielectric constant (ε_{eff}) and impedance Z_o of the microstrip to be functions of frequency. The frequency dependence of the effective dielectric constant describes the influence of dispersion on the phase velocity, whereas the frequency dependence of the effective width describes the influence of the dispersion on the characteristic impedance.

Fortunately, changes in effective dielectric constant and characteristic impedance with frequency are very small. However the frequency below which dispersion effects may be neglected is given by the relation⁽⁸⁾

$$f_{o}(GHz) = 0.3 \sqrt{\frac{z_{o}}{h(\varepsilon_{r}-1)^{1/2}}}$$
 (h in cm) (3.20)

Equation (3.20) shows that f_0 is higher for high impedance lines on thin substrates.

The numerical analysis for dispersion in open and shielded microstrip transmission lines has been treated extensively. These analyses, however, require extensive computations and fail to provide insight into the dominant physical phenomenon at work. For these reasons, the numerical approach is not convenient for microstrip circuit design and therefore, not discussed in this study.

However, there are several semi-empirical techniques available that lead to a closed form solution for the dependence of effective dielectric constant and characteristic impedance on frequency. These dispersion models are described in the following sub-sections.

3.2.1. DIELECTRIC-LOADED RIDGED WAVEGUIDE MODEL

This model for microstrip dispersion is based on the study of another structure which resembles microstrip as far as inhomogeneity of dielectric medium is concerned, but has a shape that can be analysed mathematically. ⁽⁹⁾ This structure is shown in Figure 3.4.

BOĞAZİÇİ ÜNİVERSİTESİ KÜTÜPHANES

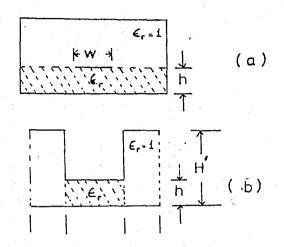


Figure 3.4. Ridged Waveguide Model for Microstrip Line

The configuration shown in Figure 3.4(b) corresponds to the microstrip cross-section shown in Figure 3.4(a). The dimensions of the structure are chosen such that it has the same electrical characteristics at zero frequency as the microstrip.

The structure is analysed for dispersion and the results are compared with the measured microstrip dispersion values to determine unknown parameter H'/h. The comparison shows that H'/h and related parameters are nearly constant or vary linearly with characteristic impedance. This feature is used to derive a simple formula that can be used to predict the dispersion of a microstrip transmission line. The resulting dispersion formula may be written as

$$\varepsilon_{eff}(f) = \varepsilon_{r} - \frac{\varepsilon_{r} - \varepsilon_{eff}(0)}{1 + (\frac{f}{f_{p}})^{2}G}$$
(3.21)

where f_p , being a parameter of the dispersion function, equals to

$$f_p(GHz) = \frac{0.398 Z_0}{h(in mm)}$$
 (3.22)

and G, being an emprical parameter used to simplify the microstrip dispersion function, equals to

 $G = 0.6 + 0.009 Z_0$

and $\varepsilon_{eff}(0)$ is the zero frequency value of ε_{eff} .

From equation (3.21), it can be seen that for $f_p \gg f$

 $\varepsilon_{eff}(f) = \varepsilon_{eff}(0)$

In other words, high-impedance lines on thin substrates are less dispersive.

(3.23)

3.2.2 PLANAR WAVEGUIDE MODEL

It has been shown (10) that the dynamic properties of microstrip can be approximated by a planar waveguide model. In this model, microstrip is represented by a parallel plate waveguide of width w_{eff} and height h as shown in Figure 3.5.

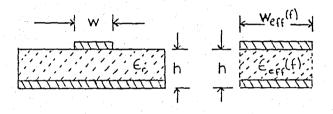


Figure 3.5. Planar Waveguide Model for Microstrip Line

The top and bottom plates are of infinite conductivity, and there are magnetic walls at the sides. It is filled with a medium of dielectric constant ε_{eff} . The value of ε_{eff} at zero frequency is determined from quasi-static analysis. The effective width w_{eff} and the effective dielectric constant ε_{eff} are frequency dependent. The frequency dependence of the dielectric constant describes the influence of the dispersion on the phase velocity, whereas the frequency dependence of the effective width describes the influence of the dispersion on the characteristic impedance. The phase velocity of the waves in microstrip line decreases with increasing frequency, hence effective dielectric constant increases with frequency. Also, the characteristic impedance of a microstrip increases with frequency. This increase in impedance can be explained only by a hypothetical decrease in the effective strip width caused by the concentration of electric field lines below the strip at higher frequency. The decrease of the effective strip width with frequency is described by the following empirical relation ⁽¹⁰⁾

$$w_{eff}(f) = w + \frac{w_{eff}(0) - w}{1 + f/f_{g}}$$

(3.24)

where

$$f_{g} = c/(2w(\epsilon_{r}))$$

 $w_{eff}(0) = effective width calculated from quasi-static analysis$

=
$$120 \text{Ih} / (Z_0 \sqrt{\epsilon_{\text{eff}}(0)})$$

And the frequency dependent impedance is given by

$$Z_{o}(f) = 120 \Pi h / (w_{eff} \sqrt{eff}(f))$$
 (3.25)

3.3. FULLWAVE ANALYSES

As pointed out in Chapter 2, the microstrip configuration is not capable of supporting a pure TEM mode, and longitudinal components of both the electric and magnetic fields are present. The hybrid modes supported by the microstrip cannot be fully described in terms of static capacitances and inductances. Therefore, one has to introduce time varying electric and magnetic fields and solve the wave equation. Moreover, the charge density used in the electrostatic analyses becomes time varying and is replaced by the electric current density for fullwave analyses. Fullwave analysis is carried out for determining the propagation constant instead of the capacitance evaluated in guasi-static analysis.

Methods of studying wave propagation on microstrip without making any quasi-static assumption may be divided into two groups. (See Figure 3.1). In one group, the microstrip is considered with a rectangular enclosure, and the other group deals with open microstrip lines. This grouping becomes convenient since different types of mathematical tools are needed for handling closed and open geometries. For example a Fourier series representation can be used to express the fields in a closed rectangular structure whereas a Fourier integral representation is suited for open structure.

IV. MICROSTRIP DESIGN CONSIDERATIONS

For design purposes it is necessary to know how the characteristic impedance, phase velocity and attenuation constant depend on geometrical factors, on the electronic properties of the substrate and conductors and on the frequency. Also, power handling capability, effect of tolerances and dielectric anisotropy are the some important design parameters.

In this section, these design parameters of microstrip lines are discussed. And various expressions, useful for microstrip design, are summarized in the last subsection called "DESIGN EQUATIONS".

4.1. MICROSTRIP LOSSES

Attenuation constant, α , is one of the most important characteristics of any transmission line. There are two sources of dissipative losses in a microstrip circuit : CONDUCTOR LOSS and SUBSTRATE DIELECTRIC LOSS. Since we consider only nonmagnetic dielectric substrates, no magnetic loss component will be present. And also since the radiation loss is a small quantity near conductor and dielectric loss, it is neglected and not considered here.

4.1.1 CONDUCTOR LOSS

Conductor loss in microstrip structure is described by Pucel (11) and Schneider (1) comprehensively. Both of these analyses are based on the "incremental inductance rule" of wheeler (12). (This method is based on the fact that inductance and conductor attenuation are related since the inductance is the normalized magnetic field energy of the circuit element and attenuation is proportional to the magnetic field energy stored in the metal conductor). In this method the series surface resistance R_s per unit length is expressed in terms of that part of the total inductance per unit length which is attributable to the skin effect, i.e., the inductance L_i produced by the magnetic field within the conductors.

It is well known that for a conductor the surface impedance, $Z_s (= R_s + JX_s)$, has a real part R_s (surface resistance per unit length) which (10) is equal to the imaginary part X_s . That is

$$R_{s} = X_{s} = \omega L_{i}$$
 (4.1)

According to wheeler, L_i can be found from the external inductance L per unit length. L_i is obtained as the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of the incrementation of

increase in L caused by an incremental recession of all metallic walls due to skin effect. This situation is shown in Figure 4.1. The amount of recession is equal to half the skin depth $\delta = (2/\omega \mu V_c)^{1/2}$.

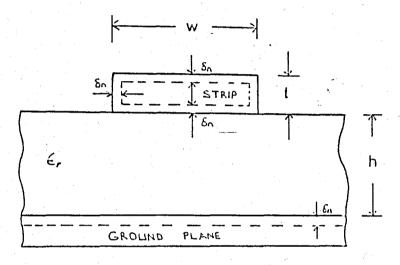


Figure 4.1. Recession of Conducting Walls of Microstrip for Loss Calculation Using "Incremental Inductance Rule"

An assumption underlying this rule is that the radius of curvature and the thickness of the conductors exposed to the electromagnetic fields be greater than skin depth. According to Wheeler (12), we have

$$L_{i} = \sum_{m} \frac{\mu_{m}}{\mu_{o}} \frac{\partial L}{\partial n_{m}} \frac{\delta_{m}}{2}$$

(4.2)

$$R_{s} = \sum_{m} \frac{R_{sm}}{\mu_{o}} \frac{\partial L}{\partial n_{m}}$$

where $\partial L/\partial n_m$ denotes the derivative of L with respect to incremental recession of wall m, n_m is the normal direction to this wall, and $R_{\rm sm} = \omega \mu_m \delta_m/2$ the surface resistance of the wall m.

The attenuation constant because of conductor (ohmic) loss is defined as

$$\alpha_{c} \stackrel{\sim}{=} \frac{P_{c}}{2P(Z)} = \frac{Power loss in conductors}{2 (Power transmitted)}$$

(nepers/unit length) (4.4)

In terms of R and Z (characteristic impedance), $\sim \alpha_{\rm c}$ may be written as

$$\alpha_{\rm C} = \frac{\left| {\rm I} \right|^2 R_{\rm S}}{2 \left| {\rm I} \right|^2 Z_{\rm O}} = \frac{1}{2 \mu_{\rm O} Z_{\rm O}} \sum_{\rm m}^{\rm C} R_{\rm Sm} \frac{\partial {\rm L}}{\partial n_{\rm m}}$$
(4.5)

Inductance L of the microstrip structure can be expressed in terms of the characteristic impedance for the microstrip with the substrate replaced by air (Z_0^a) and is given as

$$L = \frac{Z_0^a}{2}$$

(4.6)

(4.3)

where c is the velocity of electromagnetic waves in free space.

Expression for attenuation constant based on Equation (4.5) is presented later in subsection 4.5.2 where all other design information is also summarized.

4.1.2. DIELECTRIC LOSS

For a uniformly field transmission line the dielectric loss α_{du} is independent of the geometry of the line and can be written as :

$$\alpha_{\rm du} = \frac{9z_{\rm o}}{2} = \frac{\omega}{2} \sqrt{\frac{\mu}{\epsilon'}} \epsilon'' = \frac{\omega}{2} \sqrt{\frac{\mu\epsilon'}{16}} \tan \delta$$
(4.7)

where **9** is the shunt conductance per unit length of the line, ε' is the real part and ε'' is the imaginary part of the permittivity of the dielectric.

However, when the dielectric is not uniform over the cross-section of the line, the equation (4.7) does not apply. Calculation of loss for the mixed dielectric case has been considered by Schneider (13). This loss can be calculated if one knows the loss tangent of the dielectric substrate.

When the upper dielectric (air) is assumed to be lossless, the following expression for α_{d}^{2} , attenuation

constant considering mixed dielectrics, is obtained

$$\alpha_{\rm d} = \frac{\omega}{2} \sqrt{\frac{\mu \varepsilon_{\rm reff}}{2}} (\tan \delta)$$
 eff

$$= \frac{\omega}{2} \sqrt{\frac{\mu \varepsilon_{\text{reff}}}{\frac{\omega \varepsilon_{\text{reff}}}{\omega \varepsilon_{\text{reff}}}}}$$

If ${\mathfrak f}$ is the conductivity of the dielectric and ${\mathfrak f}_{{\mathfrak o}}$ the conductivity of air, we may write

$$\mathcal{F}_{eff} = q\mathcal{F} + (1-q)\mathcal{F}_{o} \cong q\mathcal{F} \quad (\text{Since } \mathcal{F}_{o} \ll \mathcal{F})$$

Also,

$$\varepsilon_{o}\varepsilon_{eff} = q\varepsilon + (1-q)\varepsilon_{o}$$
 with $\varepsilon = \varepsilon_{o}\varepsilon_{r}$

There, the Equation (4.8) becomes

$$\alpha_{\rm d} = q \left\{ \frac{\varepsilon}{q\varepsilon + (1 - q\varepsilon_{\rm o})} \right\}^{1/2} \cdot \alpha_{\rm du} = \left(\frac{\varepsilon_{\rm r}}{\varepsilon_{\rm eff}} \right)^{1/2} q\alpha_{\rm du} \quad (4.9)$$

where q is the dielectric filling fraction, and α_{du} is the attenuation constant for a line uniformly filled with the dielectric ε_{r} , given by Equation (4.7). Since,

$$q = \frac{\partial \ell_{eff}}{\partial \epsilon_r} = \frac{\epsilon_{eff}^{-1}}{\epsilon_r^{-1}}$$

(4.8)

the attenuation constant $\alpha_{d}^{}$ can be written as

$$\alpha_{d} = 27.3 \quad \frac{\varepsilon_{r}}{\sqrt{\varepsilon_{eff}}} \quad \frac{\varepsilon_{eff}^{-1}}{\varepsilon_{r}^{-1}} \quad \frac{\tan\delta}{\lambda_{o}} \quad dB/Unit length$$
(4.10)

4.2. POWER HANDLING CAPABILITY

The power handling capability of a microstrip is limited by heating caused because of ohmic and dielectric losses and by dielectric breakdown. Increase in temperature due to conductor and dielectric losses limits the average power of the microstrip line, while the breakdown between the strip conductor and ground plane limits the peak power.

4.2.1. AVERAGE POWER HANDLING CAPABILITY

The average power handling capability of microstrip is determined by the temperature rise of the strip conductor and the supporting substrate. The parameters which play major roles in the calculation of average power capability are :

(i) transmission line losses

(ii) thermal conductivity of the substrate material

(iii) surface area of the strip conductor and

(iv) ambient temperature.

Therefore, dielectric substrates with low loss tangent and large thermal conductivity will increase the average power capability of microstrip lines.

The maximum average power for a given line may be calculated from

$$P_{av} = (T_{max} - T_{amb}) / \Delta T$$
 (4.13)

where AT denotes rise in temperature perwatt and given by

$$\Delta T = \frac{0.2303h}{K} \left\{ \frac{\alpha_c}{w_{eff}} + \frac{\alpha_d}{2w_{eff}(f)} \right\} \quad (^{\circ}C/watt)$$

where K is the thermal conductivity of the substrate.

The maximum operating temperature T_{max} of microstrip circuits can be limited due to

(i) change of substrate properties with temperature(ii) change of physical dimensions with temperature and(iii) connectors.

For $T_{max} = 100^{\circ}C$, $T_{amb} = 25^{\circ}C$ and $Z_{o} = 50$ ohm, values of Average power handling capability (APHC) for various substrates at 2 GHZ, 10 GHZ and 20 GHZ are calculated by computer and given in Table 4.1. Among the dielectrics considered, APHC is lowest for poly styrene and it is maximum for BeO. At lower frequencies GaAs microstrip lines have better APHC than Si microstrip lines have better APHC than Si microstrip lines, but at higher frequencies APHC is better in the case of Si.

SUBSTRATE	HAX. AVERAGE POWER (KW)				
JUDJIKAIE	2 GHZ	10 GHZ	20 CHZ		
POLY STYRENE	0.321	0.124	"D.075		
QUARTZ	1.200	0.523	0.357		
SILI CON(SI)	3,190	2.230	1.640		
GAAS	3.550	1-470	0.930		
SAPP HIRE	11.65D	5.100	I.4i0		
ALUHINA	12.120	5.170	3.400		
BEO	174,500	75.700	51.500		

Table 4.1. Comparison of Average Power Handling Capability (APHC) for Various Substrates

4.2.2. PEAK POWER HANDLING CAPABILITY

The peak voltage which can be applied without causing dielectric breakdown determines the peak power handling capability of the microstrip. If Z_0 is the characteristic impedance of the microstrip and V_0 is the maximum voltage

the line can withstand, the maximum peak power is given by

$$P_{p} = \frac{V_{o}^{2}}{2Z_{o}}$$
(4.14)

Thick substrates can support higher voltages than thin substrates. Therefore, low impedance lines and lines on thick substrates have higher peak power handling capability.

The sharp edges of the strip conductor serve as field concentrators. The electric fieldtends to a large value at the sharp edges of the conductor if it is a flat strip and decreases as the edge of the conductor is rounded off more and more. Therefore, thick and rounded strip conductors will increase breakdown voltage.

The dielectric strength of the substrate material as well as of the air plays an important role. The breakdown strength of dry air is approximately 30 kv/cm. Thus the maximum electric field (tangential) near the strip edge should be less than 30 kv/cm. In order to avoid air breakdown near the strip edge, the edge of the strip conductor is painted with a dielectric paint which has the same dielectric constant as that of the substrate and is lossless.

4.3. EFFECT OF TOLERANCES

Characteristics of microstrip lines (namely Z_0 and ε_{eff}) are primarily functions of strip width w and substrate parameters ε_r and h. These are also influenced by factors such as strip thickness, frequency of operation (dispersion), size of enclosure etc. Any changes in the values of w, ε_r or h give rise to corresponding changes in Z_0 and ε_{eff} .

The substrate properties, like surface finish, metallization thickness, the fabrication process and so on, determine the accuracy of fabrication of strip width. In addition to the error in fabrication of strip width, the thickness and the dielectric constant of the substrate have some manufacturing tolerances. All these factors contribute to variations in Z_0 and ε_{eff} of the microstrip. Since in microwave integrated circuits (MIC's) it is very difficult to incorporate arrangements for post fabrication adjustments, it is necessary to take into account the effect of tolerances at the design stage itself. However, unlike the effects of deterministic parameters like dispersion, strip thickness, etc., the effect of tolerances cannot be incorporated exactly because of the uncertainty in Z_0 and ε_{eff} arising from tolerances.

4.4 EFFECT OF DIELECTRIC ANISOTROPY

Some of the dielectric substrates used for microstrip circuits exhibit anisotropy in permittivity. The most common examples are sapphire and Epsilom-10 (trade name for a ceramic loaded resin). In both cases, the substrates are manufactured such that one of the principal axis of the permittivity tensor is perpendicular to the dielectric interface y = h. If there were no fringing of electric fields in microstrip configuration all the field lines will_____ coincide with this axis, and the capacitance will be deter-mined by the value of permittivity in this direction. In such a case there is no effect of anisotropy.

4.5. DESIGN EQUATIONS

The numerical methods to characterize the performance of microstrip line discussed so farinvolve extensive computations. Closed form expressions are necessary for optimization and computer-aided-design of microstrip circuits. A complete set of design equations for microstrip are presented in this section. These include closed form expressions for the characteristic impedance and effective dielectric constant, and their variation with metal strip thickness, enclosure size and dispersion. Expressions for microstrip loss and quality factor Q are also described.

4.5.1. CHARACTERISTIC IMPEDANCE AND EFFECTIVE DIELECTRIC CONSTANT

The advent of high-speed digital circuitry has given emphasis to the need for a ready method of determining the characteristics of interconnection between individual components. This is particularly important for integrated circuits where the close proximity of the interconnections may induce adverse effects on the circuit performance ; for example overshoot, ringing and crosstalk. For these effects to be minimised, it is necessary to have a knowledge of the characteristic impedance of the microstriplines.

There are a number of closed form approximate expressions available for the characteristic impedance and effective dielectric constant. In this section, first a method based on line-capacitance computation (a) is described and two modifications (b,c) are given. Next, a set of equations in terms of series expansions obtained by generalization of Schneider's standard equations are given (d), and a modification to equivalent relative-permittivity, expression which takes account of the finite strip thickness is presented (e). Finally, a set of closed form expressions being more accurate and based on the works of wheeler (3) and Schneider (1) are given (f). Since a number of closed form approximate expressions are available for the characteristic impedance and effective dielectric constant, it is worthwhile to compare these results with each other and available experimental and numerical results by using tables. These tables are presented in each sub-section.

a. Line-Capacitance Computation Method

This method was pioneered by Schwarzmann (16) and based on the subdivision of the capacitance associated with a single microstripline into three components : the parallel plate capacitance, C_{pp} , between the lower surface of the conductor and the ground plane ; the fringing capacitance, C_{p} , at the edges of the conductor ; and the capacitance between the conductor's upper surface and the ground plane, C_{ppu} (See Figure 4.2),

These capacitances $C_{pp}^{}$, $C_{F}^{}$ and $C_{ppu}^{}$ are given as follows (16) :

$$C_{pp} = \frac{\varepsilon_r}{c\zeta} \frac{w}{h}$$
(4.15)

$$C_{ppu} = \frac{2}{3} \left(\frac{\varepsilon_r}{c\zeta} + \frac{w}{h} \right)$$

(4.16)

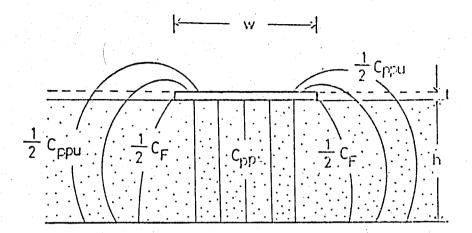


Figure 4.2. Microstripline with Associated Capacitances

and

$$C_{\rm F} = \frac{\varepsilon_{\rm r}}{c\zeta} \frac{2.7}{\log\left(\frac{4\rm h}{\rm t}\right)}$$

where ζ is the free space impedance and c is the speed of light.

As we know, for TEM mode the characteristic impedance of an elementary transmission line can be related to the velocity of propagation down the line and the capacitance per unit length by

(4.17)

$$Z_{0} = 1/\nu C$$
 (4.18)

where the velocity of propagation v is given by the relationship

$$v = c/\sqrt{\varepsilon_r}$$
 (4.19)

and

 $C = C_{pp} + C_{ppu} + C_F$

Substituting equations (4.15), (4.16), (4.17) in Eq. (4.18) yields

$$Z_{o} = \frac{\zeta}{\sqrt{\varepsilon_{r}}} \left[\frac{w}{h} + \frac{A_{1}}{\log\left(\frac{4h}{t}\right)} + \left(\frac{A_{2}}{\sqrt{\varepsilon_{r}}} - \frac{w}{h} \right) \right]^{-1} (4.20)$$

where $A_1 = 2.7$ and $A_2 = 2/3$

b. Modification to the Method Given in a :

Since one major source of error in the line capacitance computation method arises from the use of the relative dielectric permittivity, John and Arlett (17) have considered it in the straight-line approximation neglecting the dependence on microstrip geometry as follows :

$$\varepsilon_{\rm eff} = 0.4475 \varepsilon_{\rm r} + 0.6965$$
 (4.21)

They have also changed the constants A_2 in C_{ppu} and A_1 in C_F with the following emprical formulae :

$$A_1 = -0.6895 \{h/(\epsilon_{off}w)\} + 1.2163$$
 (4.22)

 $A_2 = 0.0515(h/t) + 2.183$ (4.23)

c) Modification to the Method Given in b :

In the method given in b, the expressions for A_1 , A_2 and ε_{eff} have been obtained by supposing that A_1 , associated with the fringing capacitance, is a function of the strip thickness t and the dielectric height h. Similarly, A_2 associated with the upper-plate capacitance is a function of the dielectric height h, the strip conductor width w and the effective dielectric permittivity ε_{eff} .

But there is no physical significance to believe that the constants A_1 and A_2 depend on microstrip parameters while these parameters have already been accounted for in the capacitance calculations. Also since the microwave energy propagates both in the dielectric substrate below the strip and in the air region above, the effective dielectric permittivity should be considered as a function of microstrip geometry as follows (18) :

$$\varepsilon_{\text{eff}} = \frac{\varepsilon_{r}^{+1}}{2} + \frac{\varepsilon_{r}^{-1}}{2} \left(1 + \frac{w}{10t}\right)^{-1}$$
(4.24)

Also, the capacitance C ppu between upper surface of microstrip and ground plane can be neglected since the metallic strip is thin and good conducting (18).

The fringing capacitance C_F has been evaluated by considering the round edge of the metallic strip in the method given in a. Hence, it can be calculated by taking a conducting wire parallel to the ground plane as follows (18) :

$$C_{\rm F} = \frac{\varepsilon_{\rm r}}{c\zeta} \frac{2\Pi}{\ln\left(\frac{4\rm h}{t}\right)}$$
(4.25)

Finally, the expression for the characteristic impedance comes out to be simply :

$$Z_{o} = \frac{\zeta}{\sqrt{\varepsilon_{eff}}} \left[\frac{W}{h} + \frac{2\Pi}{\ln\left(\frac{4h}{t}\right)} \right]^{-1}$$
(4.26)

Results of calculations by using the methods given in a, b and c are compared with experimental values of Kauppp (19) where w/h varies from 0.227 to 2.500 and t/h varies from 0.046 to 0.350 in Table 4.2. The results of calculations are also compare with the numerical method of Yamashita and Mettra (6) in Table 4.3. (The relative errors in percent are given in parenthesis). As it is clear from these tables, the accuracy of the line-capacitance method given in a and its derivatives is not good. Also, for effective dielectric constant, although the numerical methods predict a decrease with increase in strip thickness, the method given in c show it otherwise i.e. ε_{eff} increases with t/h. This situation can be seen from Table 4.10. This is of course not acceptable since the fraction of total energy propagating in air increases with strip thickness, there by decreasing the effective dielectric constant.

d. Generalization of Schneider's Standard Equation Obtained by Exact Conformal Mapping

The rigorous solution for computing Z_0 from equations (3.4), (3.5), (3.6) is not recommended for most engineering applications. Useful expressions for the characteristic impedance of the microstrip in terms of rational functions or series expansions have been obtained by generalization of equations obtained by exact conformal mapping as follows (1) :

$$Z_{o} = \frac{60}{\sqrt{\epsilon_{eff}}} \ln \left[\sum_{n=1}^{\infty} a_{n} \left(\frac{h}{w} \right)^{n} \right]$$

49

(4.27)

		and the second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second s	والمتعادية والمتعادية والمتعادية والمتعادية		فاستعقبتها بالموجة ويعودوهم
	т / (н	M E A S. ZD(DHH)-(19)	CALCULATED 20(0HH)		
			HETHOD A	HETHOD B	METHOD C
0.227	0.063	111.2	96,850 (-14,80)	97.763 (-13.70)	105.517 (-5.30)
0.250	0.063	111.0	101_105 (-9.90)	94.492 (-17.80)	1 11.028 (1.60)
0.340	0.063	99_2	89.489 (-10.80)	91.921 (-7.90)	101.002 (1.60)
0.483	0.090	30 . 5	76.569 (-18.10)	85.138 (-6.2)	87.505 (-3.4)
0.526	0.147	92.0	67.643 (-21.2)	79.756	75.626 (-8.40)
0.645	0.090	\$1.0	70.0353 (-15.6)	89:795 (-0.6)	82.6405 (1.90)
0.681	0.127	76.5	64.556 (-18.5)	75.729 (-1.0)	74.756 (-2.20)
0.714	0.200	73.0	57.769 (-26.3)	70.153	65.304 (-11.70)
0.909	0.127	67.05	81+229 (-15_2)	68.8869 (2.7)	76-204 (3.70)
1.157	0.147	65.0	51.205 (-26.9)	61.872 (-5.0)	62.501 (-5.90)
1.070	0.200	. 61.0	50.030 (-21.9)	61.307 (+0.5)	59.082 (-3.20)
1.000	0.280	59-4	41.682 (-19.7)	59.201 (-0.3)	54-537 (-8.70)
1.250	0.350	53.0	41.520 (-27.6)	\$2.030 (-1.8)	47.948 (~10.50)
1.875	0.350	4,2.5	34.740 (-22.3)	43.848 (13.0)	42.016 L-1.10)
2.500	0.350	36.4	29.803 (-20.5)	37.876 (+4.9)	37,429 (13,90)

Table 4.2. Comparison of Calculated and Measured Characteristic Impedances for Methods

a, b, and c ($\varepsilon_r = 4.7$)

50

•

	1	н т/н	NUM. METH.(6)	CALCULATED ZO(OHN)		
EPSR	.₩/H			HETHOD A	HETHOD B	METHOD C
1.0	0.10	0.010	253.0	312.855 (-14.80)	162.374 (-13.70)	328.083 (-5.30)
1.0	0.10	0.050	230,0	237.677 (+3.20)	317.815 (+27.60)	245.699 (6.30)
1.0	0.10	0.200	194.0	168.073 (-15.40)	274.413 (29.30)	171.508 (-13.10)
1.0	1.00	0.010	125,0	139.368 (+10.30)	117.185	183.940
1.0	1.00	0.050	122.0	122.149 (C)+2)	180.668	154.833 (13740)
1.0	1-00	0.200	112.0	100.714 (-11.2)	165.764	121.675 (7.90)
1.0	2.00	0.01	88.0	86.231 (-2.0)	89.386 (+1.5)	123.002 (28.80)
1.0	2.00	0.05	86.0	75.314 (-8.4)	172.116 (24.5)	109.740 (+21.60)
1.0	2.00	0.20	82.0	62-684 (-17-6)	115.120 (28.7)	91.970 (10.80)
11.7	0.10	0.01	96.5	45.201 (-1.3)	38-194 (-152.0)	101.201 (11.60)
11.7	0.10	0.05	¥3.0	71.614 (-24.2)	62.792 (-41.7)	74.735 (-19.00)
11.7	0.10	0.20	82.0	50.132 (~63.3)	56.72¥ (-44.5)	50.696 (-61.70)
11.7	1.00	0.01	45.0	49.347 (x.s)	25.110 (-54.5)	70.350 (+36.00)
11.7	1.00	0.05	43.7	42.151 (-3.6)	41.501 (-5.2)	54.231 (19.50)
11.7	1.00	0.20	41.5	33.688 (-23.1)	38.763 (-7.0)	30.636 (-7.40)
11.7	2.00	0.01	31.0	52.144 (3.5)	23.026 (-34.6)	48.035 (35.50)
11.7	2.00	0-05	30.4	28.927 (-5.0)	30.1493 (-0.2)	40.2876 (24.50)
11.7	2.00	0.20	24.5	24.673 (-19.5)	211.673 (-2.8)	30.614 (+3.60)

Table 4.3. Comparison of Characteristic Impedances Calculated from Methods a, b and c with Characteristic Imp. obtained by Numerical Methods (6)

and for $\omega > h$

$$Z_{o} = \frac{120 \pi}{\sqrt{\epsilon_{eff}}} \left[\sum_{n=1}^{-\infty} b_{n} \left(\frac{w}{h} \right)^{n} \right]^{-1}$$
(4.28)

The number of terms after which the series is terminated determines the accuracy of the approximations. The following formulas obtained by rational function approximation give an accuracy of ± 0.80 percent for 0 < w/h < 10which is the range of importance for most engineering applications :

For w/h < 1

 $Z_{o} = \frac{60}{(\boldsymbol{\xi}_{eff})^{1/2}} \ln(\frac{8h}{w} + \frac{w}{4h})$ (4.29)

and for $w/h \ge 1$

$$Z_{o} = \frac{120\Pi}{\left(\epsilon_{eff}\right)^{1/2} \left(\frac{w}{h} + 2.42 - 0.44 + (1 - \frac{h}{w})^{6}\right)}$$
(4.30)

The effective dielectric constant can be found by using Wheeler's method by starting from an approximate conformal mapping transformation for the transformed parallel plate capacitance (3). The square root of the effective dielectric constant $(\epsilon_{eff})^{1/2}$ obtained by this method is shown in Fig. 4.3 as a function of w/h an ϵ_r .

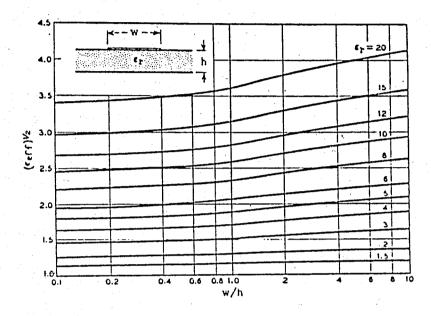


Fig. 4.3. Square Root of the Effective Dielectric Constant for the Microstrip.

In order to find a function which approximates the set of curves of Fig. 4.3 over the total range 0 < w/h < ∞ and 1 < ε_r < ∞ Schneider has defined a function F(ε_r , $\frac{W}{h}$) by

$$\varepsilon_{\text{eff}} = \frac{\varepsilon_r^{+1}}{2} + \frac{\varepsilon_r^{-1}}{2} F(\varepsilon_r, \frac{w}{h})$$
(4.31)

where

$$F(\varepsilon_r, \frac{W}{h}) = (1 + 10 \frac{h}{W})^{-1} \frac{1}{2}$$
 (4.32)

By using Eq. (4.31) in equations (4.29) and (4.30) characteristic impedance can be found.

e. Modification to Schneider's Effective Dielectric Constant Equation given in d :

The original work of Schneider (1) has considered only strips of zero thickness, a condition never achieved in practice. Yamashita and Mittra (6) have shown that the effect of strip thickness is appreciable for w/h < 1, the effect being a lowering of the characteristic impedance as found by Stinehelfer (5) by experiment. A modification to Schneider's effective dielectric constant equation has been given by Ross and Howes (20) approximately agreeing with the work of Yamashita and Mittra (6), Bryant and Weiss (21), Stinehelfer (5) and Wheeler (3). This expression is

For
$$\frac{W}{h} \leq 1$$

 $\varepsilon_{\text{eff}} = \frac{\varepsilon_r + 1}{2} + \frac{\varepsilon_r - 1}{2} (1 + \frac{10h}{w}) - \frac{1}{2}$

(4.33)

+ 0.468
$$\left(\frac{\varepsilon_r + 0.5}{1.5}\right)\sqrt{\frac{t}{w}}$$

and for $\frac{W}{h} > 1$

$$\varepsilon_{\text{eff}} = \frac{\varepsilon_{r} + 1}{2} + \frac{\varepsilon_{r} - 1}{2} (1 + \frac{10h}{w})^{-1} \frac{1}{2}$$
 (4.34)

This ε_{eff} expression is identical with strips, where the term in t is swamped by the other two w and h. It is assumed that $\frac{t}{w}$ becomes small as $\frac{w}{h}$ increases, which is likely to be true in the practical case, since it implies t/h < 0.2.

The expressions for characteristic impedance are the same as equations (4.29) and (4.30) given in d.

Results of calculations by using the methods given in d and e are compared with experimental values of Kaupp (19) where w/h varies from 0.227 to 2.500 and t/h varies from 0.046 to 0.350 and given in Table 4.4. The results of calculations are also compared with the numerical method of Yamashita and Mittra (6) in Table 4.5. (The relative errors in percent are given in parenthesis). As it is clear from these tables, the accuracy is not good for these methods, also. And just like in the method c, for the set of equations given in e, the value of ε_{eff} increases with t/h and for some set of parameters becomes even greater than ε_r . (Look at Table 4.10).

and the second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second second s				and the second second second second second second second second second second second second second second second			
W/H	тин	H E A S. ZO (OHN)- (19)	CALCULATED 20(0HM)				
			HETHOD D	METHOD E			
0.227	0.063	111.2	120.949 (+8.00)	107.180 (-3.70)			
0.250	0.063	111_0	117.436 (+5.30)	106.247 (-4.60)			
0.340	0.063	99.2	106.294 (6.60)	96.264 (-3.00)			
0.483	0.090	50.5	93.712 (3.40)	84.994 (-6.4)			
0.526	0.147	82.0	90.688 (9.5)	80.701 (-1.6)			
0.645	0-090	¥1.0	83,524 (166)	76.781 (5.46)			
0.681	0.127	76.5	81.635 (6.2)	74.176 (-3.1)			
0.714	0.200	73.0	79.997 (8.7)	71.372 (-2.3)			
0.909	0.127	67.0	71.767 (6.6)	66.089 (-1.3)			
1.157	0.147	65.D	63,499 (-2,3)	58.759 (-10.6)			
1.070	0.200	61.0	66.129 (7.7)	60.247 (-1.2)			
1.000	0.280	59.4	68.587 (13.3)	61.299 (3.0) -			
1.250	0.350	53.0	60.992 (13.10)	54.604 (2.90)			
1.875	0.350	42.5	48.827 (13.0)	44.71((4.9)			
2.500	0.350	36.0	41.016 (12.2)	41.016 (12.2)			

Table 4.4. Comparison of Calculated and Measured Characteristic Impedances for Methods d and e ($\varepsilon_r = 4.7$)

EPSR W/H	W/H	ТИН	N U H . M E T H . (6)	CALCULATED ZO(OHM)				
				METHOD D KETHOD E				
1.0	0.10	0.010	253.0	262.90 245.40 (3.70) (-3.0)				
1.0	0.10	0.050	230.0	262.50 227.30 (12.50) (-0.90)				
1.0	0.10	0,200	194.0	262.903 204.00 (26.20) (4.90)				
1.0	1.00	0.010	125.0	126.40 123.50 (1.10) (1.76)				
1.0	1.00	0.050	122.0	126.40 120.30 (3.4) (-1.4)				
1.0	1.00	0.20	112.0	126.40 115.10 (11.3) (2.6)				
1.0	2.00	0.01	83.0	89.332 87.90 (1.5) (-D.1)				
1.0	2.00	0.05	86.0	19.382 26.20 (3.7) (0.2)				
1.0	2.00	0.20	87.0	89.322 ¥3.40 (¥.2) (1.4)				
11.7	0.10	0.01	96.5	100.228 92.50 (3.7) (-4-3)				
11.7	0.10	0.05	83.0	100.728 85.00 (11.22) (-4.77)				
11.7	0.10	0.20	\$2.0	100.228 75.10 (13.10) (-4.1)				
11.7	1.00	0.01	45.0	44.308 43.70 × (-0.4) (-2.5)				
11.7	1.00	0.05	43.7	44.808 42.60 (2.4) (-2.5)				
11.7	1.00	0.20	41.5	44.808 40.70 (7.3) (-1.4)				
11.7	1.00	0.01	31.0	30.596 30.60 (-1.3) (-1.3)				
11.7	2.00	0.05	30.4	30.5% 29.60 (0.6) (-7.7)				
11.7	2,00	0.20	29.5	30.596 28.70 (3.5) (-2.7)				

Table 4.5. Comparison of Characteristic Impedances Calculated from Methods d and e with Characteristic Impedance Obtained by Numerical Methods (6).

f. New Equations

New equations with accuracy fulfilling the 1 percent goal have been obtained by modifying those of Wheeler (3) and Schneider (1). Schneider's equations for effective dielectric constant ε_{eff} are given in Eq. (4.31). Making $F(\varepsilon_r, \frac{W}{h})$ independent of ε_r is an approximation, but for $\varepsilon_r < 16$, it is good enough and the following equation gives relative errors in ε_{eff} not larger than 1 (See Table 4.7) percent for a practical range of microstrip lines (0.05 < w/h < 20 and $\varepsilon_r < 16$) :

For w/h < 1

$$F(w/h) = (1 + \frac{12h}{w})^{-\frac{1}{2}} + 0.04(1 - \frac{w}{h})^{2}$$
 (4.35)

and for
$$\frac{W}{h} \ge 1$$

 $F(W/h) = (1 + \frac{12h}{W}) - \frac{1}{2}$
(4.36)

To obtain a better approximation above it would be necessary to let F vary with ε_r . The range covered and the accuracy obtained with the approximation above should, however, be sufficient for most practical needs. (The dependence of F on ε_r decreases for increasing ε_r , thus it is belived that the largest error in the above approximation will not be above 2 % for any value of $\frac{W}{h}$ and ε_r with greatest error for w/h < 0.05).

Impedance equations for analysis are best constructed with those for single-dielectric together with the ε_{eff} equation. The error in Schneider's equation for w/h > 1 is approximately three times that claimed and efforts to improve on this showed that the best result (Look at Table 4.6) is obtained by Hammerstad (22) by modifying Wheeler's equations as follows :

For w/h < 1

$$Z_{0} = \frac{\zeta}{2\pi \sqrt{\varepsilon_{eff}}} \ln \left(\frac{8h}{w} + 0.25 \frac{w}{h}\right)$$
(4.37)

For $w/h \ge 1$

$$Z_{o} = \frac{\zeta}{\sqrt{c_{eff}}} \left[\frac{W}{h} \quad 1.393 + 0.667 \ln\left(\frac{W}{h} + 1.444\right) \right]^{-1}$$
(4.38)

where $\zeta = 120\Pi$ ohm is the free-space wave impedance.

The same accuracy has been obtained by modifying the constants of Wheeler's synthesis $(w/h = h(Z_0)$ equations as follows :

For w/h ≤ 2

$$\frac{w}{h} = \frac{8}{(exp(A) - 2 exp(-A))}$$
(4.39)

For
$$w/h \ge 2$$

$$\frac{W}{h} = \frac{2}{\Pi} \left\{ B - 1 - \ln(2B - 1) + \frac{\varepsilon_r - 1}{2\varepsilon_r} \left[\ln(B - 1) + 0.39 - \frac{0.61}{\varepsilon_r} \right] \right\}$$

$$(4.40)$$

where

$$A = \frac{Z_{0}}{G0} \left(\frac{\varepsilon_{r}+1}{2}\right)^{1/2} + \frac{\varepsilon_{r}-1}{\varepsilon_{r}+1} \left(0.23 + \frac{0.11}{\varepsilon_{r}}\right) \quad (4.41)$$

and

$$B = \frac{\epsilon_0 \pi^2}{Z_0 \sqrt{\epsilon_r}}$$
(4.42)

Effect of Strip Thickness

The equations given above assume a two-dimensional strip conductor. But in practice, the strip is three-dimensional _______ its thickness, t, must be considered. The zerothickness (t/h = 0) formulas can be modified to consider the thickness of the strip when the strip width, w, is replaced by an effective strip width, w_{eff} . Simple and accurate formulas for Z_0 and E_{eff} with finite strip thickness are (23) :

For $w/h \leq 1$

$$Z_{o} = \frac{\zeta}{2\pi\sqrt{\epsilon_{eff}}} \ln\left(\frac{8h}{w_{eff}} + 0.25 \frac{w_{eff}}{h}\right) \quad (4.43)$$

For
$$\frac{W}{h} \ge 1$$

$$Z_{o} = \frac{\zeta}{\sqrt{\varepsilon_{eff}}} \left[\frac{W_{eff}}{h} + 1.393 + 0.667 \ln \left(\frac{W_{eff}}{h} + 1.444 \right) \right]^{-1}$$
(4.44)

where for
$$\frac{W}{h} \leq \frac{1}{2II}$$

$$\frac{W_{eff}}{h} = \frac{W}{h} + \frac{1.25}{II} + \frac{t}{h} \left(1 + \ln \frac{4IW}{t}\right) \quad (4.45)$$
for $\frac{W}{h} \geq \frac{1}{2}$

$$\frac{W_{eff}}{h} = \frac{W}{h} + \frac{1.25}{II} + \frac{t}{h} \left(1 + \ln \frac{2h}{t}\right) \quad (4.46)$$

$$\varepsilon_{\text{eff}} = \frac{\varepsilon_r + 1}{2} + \frac{\varepsilon_r - 1}{2} F\left(\frac{w}{h}\right) - \frac{\varepsilon_r - 1}{4.6} \frac{t/h}{\sqrt{\frac{w}{h}}} \quad (4.47)$$

in which $F\left(\frac{W}{h}\right)$ is given by equations (4.35) and (4.36).

A summary of typical results obtained by using above equations is given in Tables 4.6, 4.7, 4.8, 4.9 and 4.10. To determine the percentage error inherent in using present equations, the available numerical results are also presented.

In table 4.6 characteristic impedance for zero thickness (t/h = 0) microstrip and in Table 4.7 effective dielectric constant for zero thickness microstrip calculated by the method given in f are compared with numerical results of Green (24), Wheeler (3) and the method given in d (another zero thickness case). As can be seen from these tables, the results for Z_0 and ε_{eff} are correct to within 1 percent (The maximum relative error in Z_0 and ε_{eff} is less than ±0.6 percent and 0.8 percent respectively) for the following sets of parameters 0.1 \leq w/h \leq 10 and $\varepsilon_{r} \leq$ 11.7 as claimed.

But in practice, the strip is three-dimensional and zero thickness case is a condition never achieved. (It may be approximated when t/h < 0.005 and 0.1 < w/h < 5). So, the zero thickness (t/h = 0) formulas given here at the beginning are modified to consider the thickness of the strip. The results obtained for microstrip including strip thickness are compared with available experimental and nemerical résults in Tables 4.8, 4.9 and 4.10. It is found

that the results for Z_o and ε_{eff} obtained by this method are correct to within 2 percent for the following sets of parameters 0 < t/h < 0.350, 0.1 < w/h < 10 and $\varepsilon_r < 11.7$.

4.5.2. EFFECT OF ENCLOSURE

Most of microstrip circuit applications require a metallic enclosure for hermetic sealing, mechanical strength, electromagnetic shielding, mounting connectors and ease of handling. Both the top cover and side walls tend to lower impedance and effective dielectric constant. This is because the fringing flux lines are prematurely terminated on the enclosure walls. This increases the electric flux in air.

The closed from equations for a microstrip with top cover (without side walls) are obtained as follows (26) :

For
$$\frac{W}{h} \leq 1$$

$$Z_{0} = \frac{\zeta}{2\pi\sqrt{\varepsilon_{eff}}} \left(\frac{8h}{w} + 0.25 \frac{w}{h}\right) - P \qquad (4.48)$$

For
$$\frac{W}{h} \ge 1$$

W/11	EPSR	1	·		
	tr'sk	NUN_NETH. (24)	WHEELER (2)	HETHOD F WITH ZERD THICK.	METHOD D
0.1	1	262.38	262.392 - (0,02)	262.94D (0.2)	262.940 (0.2)
0.2	1	221.22	221.270	111.408 (0.08)	221.408 (0.08)
9.5	1	166.67	166.697 (0.02)	1 <i>(6.</i> 872 (0.0%)	166.822 (0.03)
1.0	1	126.40	126.520 (0.1)	126.D60 (-0.2)	126.613 (0.03)
2.0	1	89.0	90.090	89.135 (0.4)	89.382 (0.5)
5.0	1	49.34	49.380 (0,1)	49.347 (0.01)	49.617 (0.5)
10.0	1	28.99	29.13	28.943 (-0.1)	29.192 (0.7)
0.1	2.62	199.68	189.960 (0.1)	190.263 (0.3)	191.010 (0.7)
0.1	2.62	158.82	158,970 (0.1)	359.190 10.2)	153.610
0.5	2.62	118,28	118,510 (0,2)	118.552 (0.2)	118-310 (0103)
1.0	2.62	88.45	88.620 (0.2)	88.763 (0.3)	88.270 (-0.2)
2.0	2.62	61.05	61.310 (1.4)	61 • 41 1 (0.5)	61.090 (0.03)
5.0	2.62	32.78	32.450 (-1.0)	32,903 (0.3)	32.870 (0.3)
10.0	2.62	18, 93	18,940 (0.2)	18.156 (-0.3)	18.912 (-D.1)
0.1	3.18	143,93	164.050 (0.1)	164.273 (0.2)	165.250
0.2	3.78	137.66	137,330 (0.2)	137.217 10.11	137.410
0.5	3.78	101.78	101.950 (0.2)	101.867 (0.08)	10[.570 (-0.2)
1.0	3.78	75.84	76.060 (0.3)	75.99 9 (0.2)	75.460 (-0.5)
2.0	3.78	52.08	52. ¥10 (1.4)	52.321 (0.4)	51.970
5.0	3.78	27.73	27.400 (-1.2)	27.831 (0.3)	27.750 (+0.1)
10-0	3.78	15.83	15.800 (U.2)	15.867 (0.2)	15. 1 90 (0.4)
0.1	9.6	108.92	109.130 (0.2)	108.597 (-0.02)	109.865 (0.8)
0.2	9.6	90.17	91,050 (0,2)	90.627 (-0.21	91.136 (0.21
0.5	9.6	67.17	67.370 10.3)	66.981 (-0.2)	66.791 L-0.6)

Table 4.6. Comparison of Characteristic Impedance for Zero Thickness Microstrip Calculated by Different Methods.

METHOD	METHOD NUN. METH. (24)		WH	WHEELER (3)		RETHOD D			HETHOD F			
EPSR W/H	2.62	3.78	9,6	2.62	3.78	9.6	2.62	3.78	9.6	2.62	3.78	9.60
0.1	1.92	2,57	5.82	1.91	2.56 (-0.3)	5.80 (-0.3)	1.89 (-1.5)	2.52 (-1.6)	5.72 (-1.6)	1.91 (-0.5)	2.56 (-0.3)	5.83 (0.2)
0.2	1.94	2.61	5,93	1.93 (-0.2)	2.60 (-0.3)	5.90 (-0.4)	1.92 (-0.9)	2.58 (-0.8)	5.90 (-0.4)	1.93 (-0.3)	2.60 (-0.1)	5.96 (0.6)
0.5	1.98	1.68	6.15	1.97	2.67 (-0.5)	6.14 (-0.4)	1.98 (+0.1)	2_69 (+0.4)	6.23 (+1.3)	1.98	2.68 (0.0)	
1,0	2,04	2.77	6.45	2.03						2.03 (-0.4)		
2.0	2.12	2.92	6.89	2.07						2.11		
5.0	2.26	3.16	7.65	2.29						2.25 (-D.7)		
10.0	2-37	3.34	8,23	2.38	3.36 (+0.6)	8.30 (+0.8)	2.38 (+0.5)	3.37	8.34 (+1.3)	2.35	3.32 (-0.6)	8.26

Table 4.7. Comparison of Effective Dielectric Constant, ϵ_{eff} , for Zero Thickness Microstrip Calcula-

ted by Different Methods.

И/ н	т / н (H E A S. 20(0HM)- (19)	CALCULATED ZO(OHM)			
		······································	NETHOD F	INCL_THICK_		
0.227	0.063	111.2	120,551 (7.7)	108.935 (-2.0)		
0.250	0.063	111.0	117.119 (+5.00)	108.850 (-1.90)		
0.340	0.063	99.2	106.229 (6.6D)	98.121 (-1.DO)		
0.483	0.090	90.5	93.906 (3.60)	\$9.824 (-1.8)		
0,526	D.147	82.0	90.936 (9.8)	82.057 (0.03)		
0.645	0.090	81.0	83,883 (3,4)	79_684 (-1,6)		
0.681	D.127	76.5	82.018 (6.7)	75.616 (-1.1)		
0.714-	0.200	73.0	80.398 (9.2)	72.616 (-0.5)		
0.909	0.127	67.0	72.222 (7.2)	67.466 (0.6)		
1.157	0.147	65.0	64.121 (-1.3)	65.211 (D.3)		
1.070	0.200	61.0	66,595 (8,4)	61.596 >^ (0.9)		
1.000	0.230	59.4	69.041 (13.9)	60,420 (1.7)		
1.250	0.350	53.0	61.683 (14.0)	53.974 (1.8)		
1.875	D.35Q	42.5	49.297 (13.8)	43.32 (1.9)		
2.500	0.350	36.0	41.198 (12.6)	36,73 (2,0)		

Table 4.8. Comparison of Calculated and Measured Characteristic Impedances for Method f with Zero Thickness and Including Strip Thickness ($\varepsilon_r = 4.7$)

EPSR W/H	W/H	Т/Н	NUH. NETH.(6)	CALCULATED ZO(OHM)		
				INCL.THICK.	ZERD THICK. (F)	
1.0	0.10	0.010	253.0	250-427 (-1-0)	262.94 (+3.7)	
1.0	0.10	0.050	230.0	226.389 (-1.5)	262.94 (12.50)	
1.0	0.10	0,200	194.0	192.251 (-1.0)	262.94 (26.20)	
1.0	1.00	0.010	125.0	125.220	126.613 (1.20)	
1.0	1.00	0.050	122,0 -	121.262 (-0.6)	126.613 (3.6)	
1-0	1.00	0.20	112.0	113.684 (1.4)	126.6L3 (11.5)	
1.0	2-90	0.01	88.0	88.706	89.335 (1.4)	
1.0	2:00	0-05	86.0	87.042 (1.1)	89.335 (3.7)	
1.0	2.00	0.20	82.0	83-184 (1.2)	89.335 (8.2)	
11.7	0-10	0.01	96.5	95.087 (-1.4)	99.313 (2.8)	
11.7	0.10	0.05	89.0	87.843 (-1.3)	99.313 (10.3)	
11.7	0.10	0.10	82.0	91.690 (-0.30)	99.313 (17.4)	
11.7	1.00	0.01	45.0	44-630 (-0.8)	45.039 (0.0)	
11.7	1.00	0.05	43.7	43.650	45.039 (2.9)	
11.7	1.00	0.20	41.5	41.880 (0.9)	45.039 (7.8)	
11-7	2.00	0.01	31.0	30.688 (-1.0)	30.975 (-0.4)	
11.7	2.00	0.05	30.4	30.231 (-0.56)	30.875 (1.5)	
41.7	2-00	0.20	29.5	29.331 (-0.5)	30.875 (4-4)	

Table 4.9. Comparison of Characteristic Impedances Calculated by New Equations (Method f) with Numerical Methods (6).

ז ט

EPSR	w/H	Т/н	EFFECTIVE DILECTRIC CONS.					
				· · · · · · · · · · · · · · · · · · ·				
			NUM MET. (25)	HET. C	HET. E	HET. F (WITH T)		
3.78	0.1	0.01	2.52	3.09	2.95	2.54		
	"	0.10	2.36	3.65	3.86 #	2.37		
"	11	0.20	-	3.70	4.42 #	2,18		
<u>, 11</u>	1-0	0.01	2.77	2.52	2.94	2.77		
"	<i></i>	0.10	2.70	3.09	3.23-	2.72		
"	<u>II</u>	0.20	-	3.32	3-41	2,66		
Ĺ	2.0	0.01	2.92	2.46	3.05	2.91		
"	· //	0.10	2.87	2.85	3.26	2.87		
"		0.20		3.09	3.38	2.83		
9.60	0.1	0.01	5.67	7.45	6.72	5,77		
	1 1	0.10	5,11	9.21	8.8E	5,24		
"	11.	0.20	-	9.40	10.18 #	4-65		
	1.0	0.01	6.42	5.69	6.91	6.47		
	11	0.10	6.19	7.45	7.53	6.31		
υ	11	0.20	-	8.17	8.01	6.12		
	2.0	0.01	6.89	5.51	7.28	6.91 🗇		
''		0.10	6.73	6.73	7 . 76	6.79		
"	11	0.20	-	7.45	8.05	6.66		

Table 4.10. Comparison of Effective Dielectric Constant, ϵ_{eff} , for Microstrip Including Strip Thickness Calculated by Different Methods

$$Z_{o} = \frac{\zeta}{\sqrt{\epsilon_{eff}}} \left[\frac{w}{h} + 1.393 + 0.667 \ln\left(\frac{w}{h} + 1.444\right) \right]^{-1}$$

$$- \left[1 - \tanh\left(1 + \frac{0.48\sqrt{\frac{w}{h} - 1}}{\left(1 + \frac{h'}{h}\right)^{2}}\right) \right] \cdot P$$
(4.49)

where

$$\varepsilon_{\text{eff}} = \frac{\varepsilon_r + 1}{2} + \left(\frac{\varepsilon_r - 1}{2} + \frac{\varepsilon_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) + \left(\frac{\omega_r - 1}{h}\right) +$$

and

$$P = 270 \left[1 - \tanh(0.28 + 1.2 \sqrt{\frac{h'}{h}}) \right]$$
 (4.51)

The factor $F(\frac{w}{h})$ has been defined in the equations (4.35) and (4.36); h' is the spacing between the strip and the top cover and $\frac{h'}{h} \ge 1$.

4.5.3. EFFECT OF DISPERSION

The effect of frequency (dispersion) on ε_{eff} is described accurately by the dispersion model given by Getsinger (9) and modified by Edwards and Owens (27), as discussed in Section 3.2. The effect of frequency on the characteristic impedance of the microstrip has been described by several investigators (28, 29, 30, 31). Among these, Bianco et. al. (30) has approximate results closer to numerical values.

The results of Bianco et. al. for $Z_0(f)$, and of Edwards and Owen for $\epsilon_{eff}(f)$ may be stated as follows :

$$Z_{o}(f) = Z_{T} - \frac{Z_{T} - Z_{o}}{1 + G\left(\frac{f}{f_{p}}\right)^{2}}$$
 (4.52)

$$\varepsilon_{\text{eff}}(f) = \varepsilon_{r} - \frac{\varepsilon_{r} - \varepsilon_{\text{eff}}}{1 + G\left(\frac{f}{f_{p}}\right)^{2}}$$

where

$$G = \left(\frac{Z_{o} - 5}{60}\right)^{\frac{1}{2}} + 0.004 Z_{o}$$
(4.54)

$$f_{p}(GHZ) = \frac{6.16 \times 10^{3} Z_{o}}{h}$$

Here h is in cm, Z_0 is in ohms and Z_T is twice the characteristic impedance of a stripline of width w and heihgt 2h. Z_0 and ε_{eff} are quasi-static values obtained earlier.

(4.53)

4.5.4 LOSSES

A closed form expression for total loss can be derived using Equations (4.43-4.44) as follows :

$$\alpha_{\rm T} = \alpha_{\rm c} + \alpha_{\rm d} \tag{4.56}$$

The two components α_c and α_d are given by for $\frac{w}{h} \leq 1$

$$\alpha_{c} = 1.38 \text{ A} \frac{R_{s}}{hZ_{o}} \frac{32 - (w_{eff}h)^{2}}{32 + (\frac{w_{eff}}{h})^{2}} dB/cm$$
 (4.57)

For
$$\frac{W}{h} \ge 1$$

$$\alpha_{c} = 6.1 \times 10^{-5} A \cdot \frac{R_{s}^{Z} \circ \ell_{eff}}{h} \left(\frac{W_{eff}}{h} + \frac{0.667 \frac{W_{eff}}{h}}{h} + \frac{0.444}{h} \right) dB/cm$$

(4.58)

$$\alpha_{d} = \begin{pmatrix} 4.34\zeta \sqrt{\frac{\varepsilon_{eff}^{-1}}{\sqrt{\varepsilon_{eff}}(\varepsilon_{r}^{-1})}} & dB/cm\left(\frac{w}{h} \le 1\right) \\ \sqrt{\varepsilon_{eff}}(\varepsilon_{r}^{-1}) & (4.59) \\ 27.3 \frac{\varepsilon_{r}}{\varepsilon_{r}^{-1}} & \frac{\varepsilon_{eff}^{-1}}{\sqrt{\varepsilon_{eff}}} & \frac{\tan\delta}{\lambda_{o}} & dB/cm\left(\frac{w}{h} \ge 1\right) \end{pmatrix}$$

where

$$A = 1 + \frac{h}{w_{eff}} \left(1 + \frac{1.25}{\Pi} + \frac{1.2B}{t} \right)$$

 $R_{s} = \frac{\Pi f \mu_{o}}{\rho_{c}}; \rho_{c} = resistivity of the strip conductor$

 $\int = \omega \varepsilon_0 \varepsilon_r \tan \delta = \text{conductivity of the dielectric}$ substrate

and

$$B = \begin{cases} h & \left(\frac{W}{h} \ge \frac{1}{2\Pi}\right) \\ 2 \Pi W & \left(\frac{W}{2} \le \frac{1}{2\Pi}\right) \end{cases}$$

The dielectric loss is normally very small compared with the conductor loss for dielectric substrates. The dielectric loss in silicon substrate (used for monolithic MICs), however, is usually of the same order, or even larger than the conductor loss, this is because of lower resistivity available in silicon wafers. However, higher resistivity can be obtained in GaAs, and therefore the dielectric loss is lower for this material.

Values of conductor and dilectric losses per unit length for 50 ohm microstrip lines on various substrates (dielectric as well as semiconductor) are plotted in Figure 4.4 as functions of frequency. At a given frequency the total loss can be obtained by adding the two values.

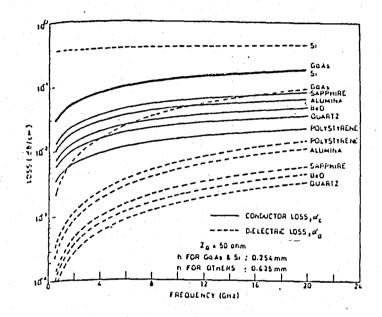


Figure 4.4. Conductor and Dielectric Losses as Functions of Frequency for Microstrip Lines on Various Substrates.

4.5.5. QUALITY FACTOR

The quality factor, Q, of a microstrip can be related to the total loss in the line by (32)

$$Q_{\rm T} = \frac{\beta}{2 \alpha_{\rm T}}$$

(4.60)

where $Q_{\rm T}$ is the equivalent Q of the resonator (quarter wavelength), $\alpha_{\rm T}$ is the total loss in the resonator, and $\beta = 2\pi/\lambda_{\rm m}$. When losses in a resonant line are considered, another loss factor, $\alpha_{\rm R}$, due to radiation at the open end discontinuities must also be taken into account. The corresponding radiation Q-factor is given by (32)

$$Q_{\rm R} = \frac{Z_{\rm O}}{480\,\Pi \cdot \left(\frac{\rm h}{\lambda_{\rm O}}\right)^2 \cdot \rm R}$$

where

$$R = \frac{\varepsilon_{eff}(f) + 1}{\varepsilon_{eff}(f)} - \frac{\left[\varepsilon_{eff}(f) - 1\right]}{2\left[\varepsilon_{eff}(f)\right]^{3/2}} \ln \left[\frac{\left[\varepsilon_{eff}(f) + 1\right]}{\left[\varepsilon_{eff}(f)\right]^{3/2}}\right]$$
(4.62)

in which $\varepsilon_{eff}(f)$ is given by the Eq. (4.53). The total Q of the resonator can be expressed by

$$\frac{1}{Q_{\rm T}} = \frac{1}{Q_{\rm c}} + \frac{1}{Q_{\rm d}} + \frac{1}{Q_{\rm R}}$$
(4.63)

Here Q_c , Q_d and Q_R are the quality factors corresponding to conductor, dielectric and radiation losses, respectively. Finally, the circuit quality factor Q_o , is defined as

$$\frac{1}{Q_0} = \frac{1}{Q_c} + \frac{1}{Q_d} = \frac{\lambda_0 (\alpha_c + \alpha_d)}{\Pi \sqrt{\epsilon_{eff}(f)}}$$
(4.64)

(4.61)

The variation with frequency of $\rm Q_{_O},~Q_{_R}$ and $\rm Q_{_T}$ for a quarter wave resonator on different substrates is shown in Figure 4.5.

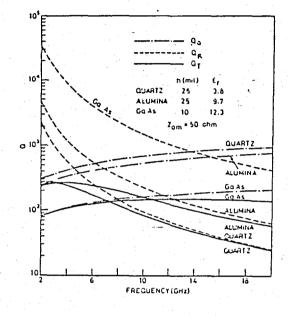


Figure 4.5. Variation of Q-factors with Frequency for Quarterwave Microstrip Resonators.

V. MICROSTRIP MEASUREMENTS

Just as in case of any other transmission structure the important characteristics that need be measured for a microstrip are :

- (i) characteristic impedance
- (ii) phase velocity and
- (iii) attenuation constant

Also, in several cases, the dielectric constant of the substrate material is not known accurately. Since this information is required for microstrip circuit design, several methods have been devised for quick determination of the dielectric constant of metallized substrates.

In this chapter, the methods for the measurement of microstrip characteristics and for substrate dielectric constant are briefly outlined.

5.1. SUBSTRATE DIELECTRIC CONSTANT

In the normal course of fabricatingdielectric substrates for MICs, a dielectric filled resonator cavity is automatically constructed. (The substrate is metallized on each side, hence forming a tiny resonant cavity). The rectangular substrate with its top-and bottom-surface metallization (sides not metallized) becomes, in effect, a parallel plate dielectric-loaded-waveguide resonator. This structure is shown in Figure 5.1(a). For high dielectric constant substrates the fringing field is very small, and the sides of the resonator are good approximations to open circuits. The boundary conditions, therefore, consist of an open circuit at the side walls of the resonator.

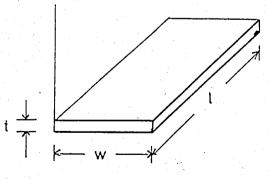


Figure 5.1(a) Metallized Substrate as a Parallel Plate Resonator

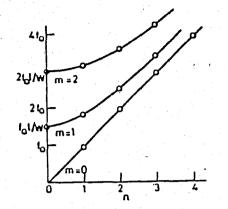


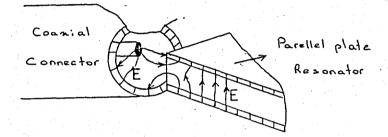
Figure 5.1(b) Resonance Frequencies for Various Modes of a Metallized Substrate Resonator (from (33)).

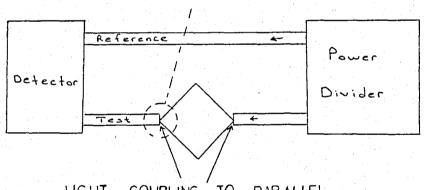
The resonance frequency f_{mn} for a wavequide with open-circuit side walls are given by

$$f_{mn}^{2} = \frac{c^{2}}{\varepsilon_{r}} \left\{ \left(\frac{m}{2w} \right)^{2} + \left(\frac{n}{2\ell} \right)^{2} \right\}$$
(5.1)

where m and n represent the mode of resonance and correspond to the number of half cycle variations along w and l, respectively. Values of f_{mn} are shown in Figure 5.1(b) as dots superimposed on the dispersion curves.

Excitation of the resonator at the substrate corner and detection of resonance are accomplished as shown in Figure 5.2 (33). Transmission measurements may be carried out by using a network analyser or any other suitable system (sweep generator and crystal detector etc.). The modes are identified by referring to Figure 5.1(b).





T

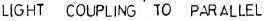


PLATE RESONATOR

Figure 5.2. Test Configuration for Resonance Measurements. The accuracy of this method is limited because of the fringing field and radiation due to the open sides of the resonator. A modification has been suggested (34) wherein the substrate is metallized on all the sides so that a small microwave cavity is formed. Equation (5.1) for various resonant frequencies is still valid. Resonant frequencies are measured by clearing metallization from the corners of the cavity and positioning the center conductor in coaxial connectors as shown in Figure 5.2.

5.2. CHARACTERISTIC IMPEDANCE

Impedance is a fundamental concept in microwave circuit design because the impedances of circuit elements and their interconnections determine the distribution of power within a circuit. The ability of a microwave engineer to predict circuit performance will partially depend on the accuracy of the knowledge of impedances for available circuit elements.

The characteristic impedance can be measured by terminating the microstrip with a precision coaxial load and measuring maximum and minimum VSWR as a function of frequency. With Z_{OR} as the reference line impedance (50 ohms) the characteristic microstrip line impedance Z_{O} is determined by

$$\left(\frac{z_{o}}{z_{OR}}\right)^{\pm 1} = \sqrt{VSWR_{max} VSWR_{min}}$$
(5.2)

where the exponent +1 goes with high impedance lines, -1 with low impedance lines. Since the general behavior of Z_{O}/Z_{OR} as a function of geometry is known from Time Domain Reflectometry (TDR) measurements as well as from previous theoretical and experimental results, the question whether to use +1 or -1 never arises.

5.3. PHASE VELOCITY OR EFFECTIVE DIELECTRIC CONSTANT

Phase velocity or effective dielectric constant can be determined by using Reflection Cancellation Method (35) which is based upon the fact that a section of mismatched transmission line of length ℓ will appear to be a perfect match at frequencies such that $n\lambda/2 = \ell$. At other frequencies the line is mismatched. If the source frequency is adjusted the line will appear to be matched at frequencies such that $\ell = \lambda_1/2$, λ_2 , $3\lambda_3/2$, etc., thus allowing λ_1 , λ_2 , λ_3 , etc. to be obtained. The phase velocity v_p is given by

$$v_p = f\lambda = c/\sqrt{\epsilon_{eff}(f)}$$
 (5.3)

where c is the velocity of light in free space. Thus, at the matching frequencies

$$\varepsilon_{\text{eff}}(f) = \left(\frac{c}{f\lambda}\right)^2$$

which allows $\varepsilon_{eff}(f)$ to be found. When dispersion effects are negligible, Equation (5.4) gives the value of ε_{eff} . In the case of significant dispersion the value of $\varepsilon_{eff}(f)$ obtained at the lowest frequency is used as a first approximation to ε_{eff} .

In this method, The frequencies at which the reflection coefficient at the input to the mismatched section is zero are determined using a network analyzer and the length *l* of the microstrip line is measured. This method is quite simple to apply and is not wasteful of substrate material. It can also determine the permittivity associated with a specific section of microstrip.

5.4. ATTENUATION CONSTANT

The most satisfactory method of measuring the attenuation constant for low-loss substrates is from the Q-factor of a resonant section of line. The attenuation constant and the unloaded quality factor Q_0 are related by the following expression

$$\alpha = \frac{27.3}{Q_o \lambda_m} \quad (dB/cm)$$

(5.4)

(5.5)

An approximate but very simple method to measure the attenuation constant is based on the comparison technique. In this method two microstrip lines with identical electrical characteristics but different lengths are taken. Their insertion losses are measured. The difference between the two values of insertion loss is used for evaluating the attenuation constant. This procedure avoids the systematic errors caused by radiation, coaxial to microstrip transition, and so forth.

VI COMPUTER AIDED DESIGN OF MICROSTRIP LINES

6.1. PROGRAM FOR MICROSTRIP DESIGN

A complete set of design algorithm for microstrip is presented in this program. This includes closed form expressions for the characteristic impedance, Z_{0} , and effective dielectric constant, ε_{eff} , and their variation with metal strip thickness, enclosure size and dispersion. Expressions for microstrip loss and quality factor Ω are also given.

Programming language is FORTRAN and the equations for Z_{o} and ε_{eff} given in this are correct to within 2 percent for the following sets of parameters : $0 \le t/h \le 0.350$, $0.1 \le w/h \le 10$ and $\varepsilon_{r} \le 11.7$

6.2. COMPARISON BY A COMPUTER PROGRAM USING GRAPHS

A computer program ensuring to make a comparison of characteristic impedance or effective dielectric constant obtained from different approaches with each other for desired t/h and w/h ratios and for different ε_r 's by using a special plot algorithm is given here.

```
............
      FROURIN FOR
                   - FICROSTRIP
                                 DESIGN
 PROCEAR ASTRP (GIADI/VERI/TAPES=GIRDI/TAPES=VERI)
υΑΤΑ ΕΡSRAADHAAT FREWARESOSCACODS/X12X22X32X42X52X02X72X0
        : STRIF CONDUCTOR WIDTH (IN CH)
И
          SUESTRATE THICKNESS (IN CH)
H
          SPACING BETWEEN STRIP AND TOP COVER
hř
          STRIF CONDUCTOR THICKNESS (IN Ch)
T
        :
          VELOCITY OF LIGHT IN FREE SPACE
C
        :
        : OPERATING FREQUENCY (IN HZ)
FREG
        : RELATIVE PERMITTIVITY
FPSR
EPSO
        : PERMITTIVITY FOR FREE SPACE
        : FREL SPACE FERHEABILITY
FSP
RESESC : RESISTIVITY OF STRIP CONDUCTOR
        : CUNDECTIVITY OF DIFLECTRIC SUBTART
CCDS
C=3E10
EPS C = 3, 85 42 EH 14
FSP=(41-9)+3.1415
RAT kh=u/n:
RATHFEEC
R+TTF=T/n
 * * * * * * * * * * * * * * * * *
    CHARTCHERISTIC IMPEDANCE AND EFFECTIVE DIELECTRIC
         CONSTANT FUR ZERU THICKNESS NICROSTRIP
          EPSEE : LEFECTIVE DIELEKTRIC COSTANT FOR FETHED F
       CHARECTERISTIC IMPEDANCE FOR METHOD F
 2 D E -
1E(R)TWH_LL.1) EPSEF=(((), / SURT()+()2/RATUR)))+(0.14*(()+
8RATHA) **2)))*((EPSR-1)/2))*((EPSR+1)/2))
IF(#ATWH. GT.1) EPSEF=(((EPSR-1)/2.)*(1./SWRT(1+(12./
3EATKE))))+((CFSR+1)/2)
IF(FATHHULL 1) ZUF=(ALOG((& /RATHH)+(A.25*RATHH))))*
& (60_/SQR1 (EPSEF))
IF(RATWH_GT_1) ZUF=(1./(KATWH:1.395+0.067*(AL0G(1.444+
(376_874F))) + (376_8754FT(EPSEF))
          ** ** ** ** ** ** * * * * * * * * *
      EFfeCT
              °C F
                  STRIP THICKNESS
              **********
                     CONST. INCLUDING STRIP THICKNESS
EPSEFT : FFF. DILL. CONST. INCLUDING ST
RATWHE : RATIC OF W 10 HE (RATWHE=W/HE)
        : ZU FOR MICROSTRIP INCLUDING STRIP THICKNESS
ZCST
X=1 _/(2*3(22/7))
IF(FATWH_LE_1) EPSEFT=((((1,/SuRT(1+(12,/RATWH)))+
$(0,C4*((1-6AT,H)**2)))*((FFSK-1)/2,))+((EPSR+1)/2))
&- ( ( ( EPSR-1) /4 _c ) * (KATTH/SURT(RAT#H) ) )
IF(FATWH.GT.1) EPSLFT=((((LPSR-1)/2.)*(1./SURT(1+
8(12,/RATWH))))+((EPSR+1)/2,))-(((EPSR-1)/4.0)+(RATTH
2/SuRT(RATUR)))
IF(RATUH_LL.A.) RATUHE=((1+(ALOG(12.504+(RATWH/RATH
8)))) * (RATTH*U,39780))+RATHH
IF(RATWH_GT_A) RATWHE=RATWH+((1+ALOG(2./RATT))*(
60.39788+KATTH)).
 IF(RATWH_LE_1) ZUST=(ALOG((B./RATWHE)+(C.25*RATWHE)))
$ * (60/SURT (EPSET)))
 IF(RATHF_GT_1) 2UST=(1_/(RATWH)+1_393+(3_667*(ALUG
&(1,444+RATAHE))))=(376.8/S4RT(FPSEFT))
```

LIFECT OF LICLOSURE ******* EPSEFE : FFF, DILEC. CONSTANT FOR AN ENCLOSED MICROSTRIP RATHEN : RATIC OF HE TO H S (HE/H) >10 ZAZ : CHARACTERISTIC IMP. FUR AN ENCLOSED MICROSTRIP RAT NEH= HE/H IF(RATHH, LE, 1) EPSEFE=((((1/SURT(1+(12/RATHH)))+(C, C4*((1+ \$RATWE)**2)))*((@P36-1)/2))TANH(0, 16+(0, 235*RATHEH)-(0, 415/ 3((RATHEH)**2))))+((EPSR+)/2) IF(KKH_GT_1) FPSEFF=((1/SQRT(1+(1?/RATKH)))*(TANH(0.13+(302235*RATHEH)-CR2415/CCRATHEH)**2))))+CCEPSR+1)/2) IF(RATWH, LF. 1) 208=(((3/RATWH)+(0,25*RATWH))*(50/SUPT(EPSFFF 8)))-27J*1-(TANH(6u28+(1u2*SuFT(RATHEH))))) IF(FATUR, GT.1) 20 E=((1/(RATUR+1.393+(0.007*(ALUC(RATWR+1.444 k 4 Γ H E H J J J J J A (1+ C T A K H (1+ C (U ₄ 4 2 × C S G R T C R A T E H-1 J J) / C (1 + K A T H L H J と**2))))))) ******* LEFECT OF DISPERSION (FREQUENCY) * *********** 2:10 : LFF, DILEC, CHSTART INCL, EFFECT OF DISPERSION-200 : CHABLCTERISTIC INP. INCL.EFFECT OF DISPENSION 2.0 : TWICE THE CHARICTERISTIC INF. OF ASSTPICINE OF WIDTH & AND FOIGHT 2H FREK=FRE4/1E9 RAT&FD=(%/(2×n)) ΙΕ(ΚΑΤΝΗ_LE(1) ΖυΤ=2*((ΑΔΟG((8,/ΚΑΤΥΗ)+(υ,25*ΡΑΤΝΗ)))*(δυυ S/SURT(EPSE))) IF(PATER_J]_1)_2UT=2+(1./(RATWH+1.393+0.067*(ALCG(1.444+ 88768)))))*(376.376187676567))) EPSEF0=EPSE+((EPSR+EPSLF)/((((PRLK/((15+66×20F)/H))**7)*(2SURT((2CE+5)/20)+(0_104+20E)))+1)) 290=291-((291+27F)/((((FRK/((15,56+20F)/H))**C)*(SUFT((とてびドーシンノ ビジャレク。 ビレイキ ビドンシンナキンシ ****** CSSES Ł CLOSS : CONDUCTOR LOSS DEOSE : DILECTRIC LOSS TLUSS : TOTAL LOSS IF(RATAH_GT_A) EQU=1+((1/RATWHE)*(1+(0.398*(ALOG(?/RATTH))))) 1F(RATWH_LE4) E2U=1+((1/RATWHE)+(1+(U_398+(ALC3(12)50*(PATWH 2/RAT1H)))))) 1F(RXTWH_LE_1) CLOUS=(1,38*54U)*(S4RT((3,14*FFE4*FSP)/R7505C) 6/(H * 202 T)) * ((32-((R + TWHE) * * 2))/(32+((RATWHE) * * 2))) IF(RATWH_GT_1) CLOSS=(RATWHE+((0.667*RATWHE)/(RATWHE+*,444)))* 8(3_0L3.61+E3U)*(((SGRT((3_14*FREG*FSP)/RESOSC))*235T*EPSEFT)/h) IF(RATWH_LL_1) DLOSS=1036.14*CODS*((LSEFT+1))/(SAPT(EPSEFT)*(2EPSR-1))) IF(R/TWF_GT_1) DLOSS=27,3*(EPSR/(EPSR+1))*((EPSFET+1)/SQKT &(EPSEFT)) *((CCUC/(C.28*FREU*EPSA*EPSR))/(C*FR[u)) TLUSS=CLUSS+DLOSS

```
QUALITY
                        EACTOR
     FUULVALENT & OF THE RESONATUR
4T
   :
     QUALITY FACTOR CORRESPONDIG TO CONDUCTUR LOSS
J C
   :
     QUALITY FACTOR CORRESPONDING TO DIELECTRIC LOSS
JD
   :
   : QUALITY FACTOR CORRESPONDING TO RADIATION LOSS
JR
   : CIRCUIT CUALITY FACTOR
u fi
uT=(cu28+FREu+(SuRT(EPSEFT)))/C
RAD = ((L PSEFD+1) / EPSEFD) ~ ((((L PSEFD-1) **2) / (2*SuRT(LPSFFD**3)))
* (ALCG((SWRT(EPSEFD)+1)/(SWRT(EPSEFD)-1)))
QR= (20F/(486×3,14×((H/(C×FKEQ))**2)*KAD)
un= (3.14*Surt (LPSEFD))/ ((C*FREu)*(CLOSS+DLOSS))
STOF
END
```

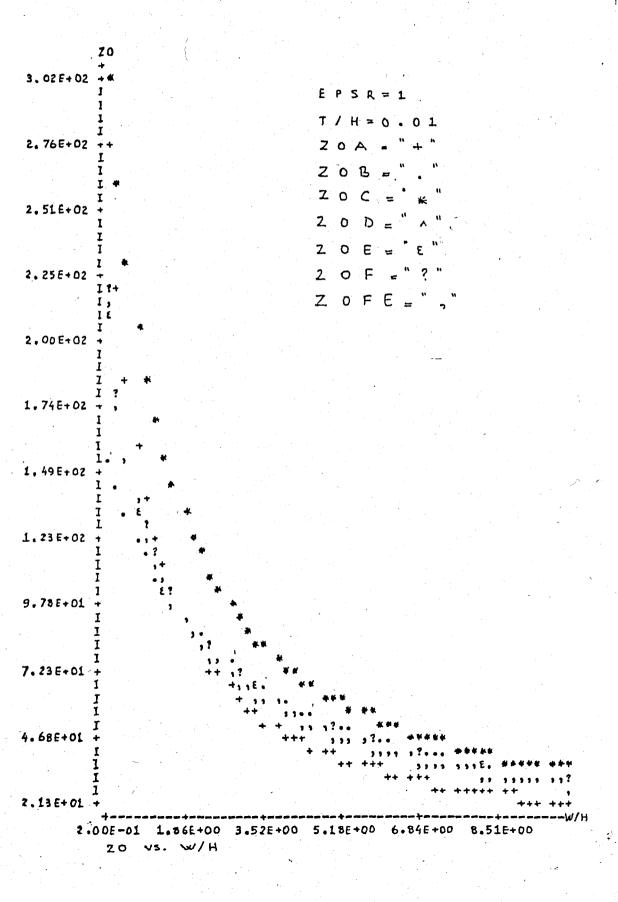
```
F
                       Ω
                          R
                              KAK
                                    ING
                                             C
                                               O P P A
                                                       RI
                                                             5 0
    F.
      1:
        J 56 K
               4
                                                                1.
                                       GRAPHS
                   1Ì
                     ì
                          u
                            S
                              I.N.G
 ΡΑΘΕΚΑΛ, ΓΣΥ (ΙΝΡΟΤΖΟΟΤΡΟΤΖΊΑΡΙ 5= ΙΝΡΟΤΖΙΑΡΙ 6= ΟΟΤΡΟΤΣ
 DIRENSION 20x (20) / 20E (20) / 20E (20) / 20D (20) / 20E (20) / 20F (20)
 DIMENSICH ZREE(SU), IN(7), X(7, CÚ), Y(7, CU)
      CHARACTERISTIC INF. FOR METHOD A
 2 6 K
      CHARACTERISTIC THP. FOR HETHUD
 205
                                         а
                       IMP. FOR HETHOD C
 ZCC
      CHARACTER TS F1 C
                       IMP_ FOR NETHOD D
 200
      : CHARACTEKISTIC
      CHARACTERISTIC INP. FOR HETHOD E
CHARACTERISTIC IMP. FOR HETHOD F
 ZOE
 2 () F
 ZCFE :CHA. IMP. FOR FET. F INCLOING THICKNESS
 EPSR=11.7
 RATkFE=C
 ドメエット=0
 RATTE=0.01
 DC 21 1=1,50
RATER=RATERT
EPSEFARTPSK
 20A(1)=(376,8750RT(EFSR))+(1,7(RATWH+((0,6067
BOURT(EPER))*RATAB)+(Ex7/ALOG10(4x/EATTH))))
EPSEF3=(0_4475+EPSR)+0_6965
 А1= (C_0515* (1/к XTTh))+2_183
 x2= (+ C_ 2295 * ( 1/ (2 PSE FB* RATWH) )) +1 _2103.
 206(1)=(376,8759RT(FFSEFB))*(127(RATWH+(A17(AL0619(47
IRATTEDID+((#2+RATWH)/S-RT(LPSEFB))))
 EPSEFC=((1,/((KATNH/(10+*KKTTH))+1_))*
$((CF2R+1)/2.))+((CF2K+1.)/2.)
 ZCC(1)=(376.E/SORT(EFSEFC))*(1_/(RATNH+(6.E62/(ALC6
3(4_/6477n)))))
EPSTFD=0_5+((EPSR+1)+((EPSR-1)+(1)/SUR1(1+(10./RAT#H)))))
 IF(R/THH_LL_1)/200(I)=ALOG((8_/RATHH)+(RATHH/4_))*
$(CU/(SURT(LFSEFD)))
 1F(EATER_GT.1) ZUD(1)=370.8/((((1-(1/FATER))++5)-(0.44/
*RATEE)+2.42*RATWH)*(SURT(EFSEFD)))
 IF(RATWH_LE_2) EPSEFE=((EFSR+1)/2)+(((EPSR-1)/2)+(1+/
ISURT (1+ (1 R/ RATWH) )))+(U, 400+((EPSR+0, 5)/1.5)+(SURT
I(RATIN/RATUR)))
 IF(RATWH_CT_2) EPSEFL=((LFSR+1)/2,)+((EPSR+1)/2,)+(1./
6(S1RT(1+(1U,/5KTWH))))
 IF(RATEH_LE_1) 20E(I)=ALUG((G_/RATEH)+(RATEH)
34.))*(00./(SuRT(EPSEFED))
 IF(R#TWH.GT.1) ZUE(I)=376.c/((((1-(1_/FATWH))**C)
3- (J . 44/ RATWH) +2 .4 2+ FATWH) + (SURT (EPSEFF) ))
 IF(RATWH_LE_1) EPSEFF=(((1,/SURT(1+(12/RATWH)))+
$(C, C4*((1-RATHH)**2)))*((FPSR-1)/2))*((FPSR+1)/2,)
 IF(RATHE.GT.1) EPSLFF=(((EPSR=1)/2.)*(1./Sukt(1+(12./
&RATWH))))+((EPSR+1)/2)
 IF(RATWH_LE#1) ZUF(J)=(ALOG((8./RATWH)+(0.25*PATWH
8))) = (cu_/SURT(EPSTEF))
```

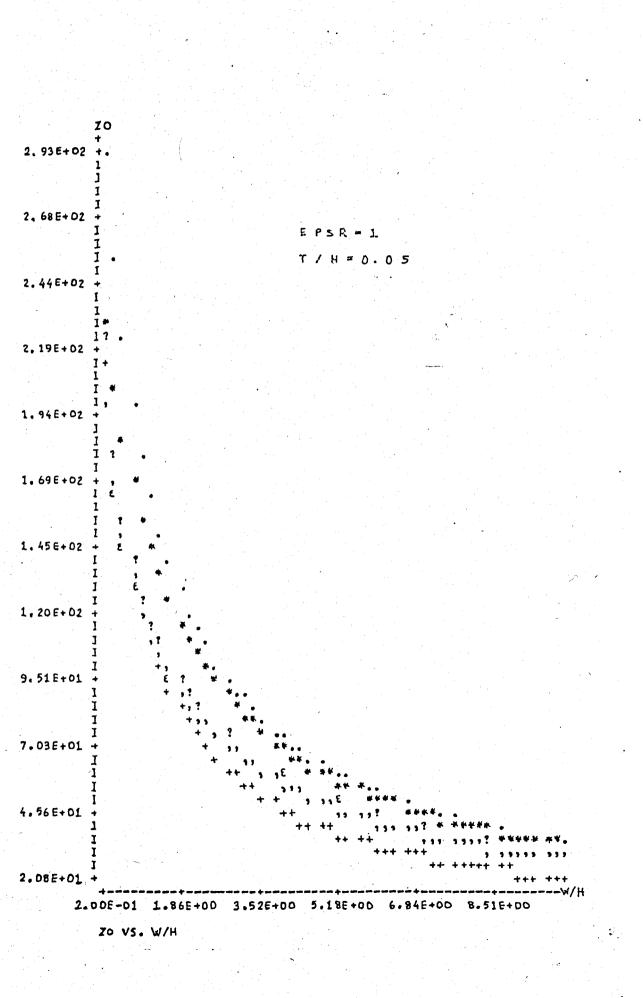
```
1F(F,Tuh, GT,1) ZOF(I)=(1,V(RATWH+1,393+0,607*(ALUG(
   SIJ444+RATHH)))) *(376_8/SURT(EPSEFF))
    A=0.15915494
    IF(RATWH_LL_1) EPSLF6=((((1./SuRT(1+(12./RATWH)))+
   $(0,C4*((1+k/TkH)**2)))*((TPSk-1)/2,))+((LPSR+1)/2,))+((
   3EPS 8+1) /4 ....)* (KAT (H/SURT(RATWH)))
    IF(RATWH_GT_1) EPSLFE=((((EPSR-1)/2.)*(1,/SURT(1+
   3(12,7KATHH))))+((EPSK+1)/2,))+(((EPSK+1)/4,6)*(RATTH
   8/SURT (RATUN))).
    IF(RATWH_LL_A) RATWHL=((1+(ALCG(12,564*(RATWH/
   2RATTH)))) * (RATTH* 0, 35788))+RATWH
    IF(RATWH_GT_A) PATWHE=RATWH+((1+ALUG(2_/RATTH
   3)) * ([.39782 *RATTH))
    IF(RATWH_LE_1) ZUFE(1)=(ALOG((8_/RATWHE)+(0_25*
   LRATHHE))) *(6U/SURT(EFSEFG))
    IF(R/TWH_GT_1) ZUFE(I)=(1./(RATWHE+1.393+(U.667*
   5(ALQC(1,444+RA101E))))*(376,8/SURT(LPSEEG))
    X(1 > 1) = R \wedge T W H
    x (2,1)=6ATWH
    x (5,1)=RATWH
    X (4,1)=RATWH
    X (S, J) = RATWH
    X (0/1)=RATAH
    X (7,1)=FATH
    Y(1,1) = 2U + (1)
    Y(2,1) = 209(1)
    Y(3/1) = ZUC(1)
    Y(4 > 1) = 20 D(1)
    Y(5>1)=ZUE(T)
    Y(0 > 1) = 20F(1)
    Y(7/1)=20FL(1)
20
    CONTINUE
    18(1)=50
    IH(2)=50
    IN(3)=50
    IN(4)=50
    エル(ち)ミンロ
    IN(6)=5P
    IN(7)=50
    CALL GRAFTK (EU, 56, X, Y, IN, U, 7)
    WRITL(0,169)
    FORMAT(///// 15% + 20 VS. W/H 1//)
1.09
    STUP
    END
    SUBROUTINE GRAFIC(1X, IY, X, Y, IN, NL, ID14)
   :LENGTH OF X-+XIS
      Iх
           LENGTH OF Y-AKIS
      ΙY
           :INDEPENDLAT VARIAELE
   *
      x
            :DEPENDENT VARIABLE
      Y
     · 1 h
            :NUFELR OF POINTS
   4
            :LOGARITHHIC INDICATOR
   * 1
     THE
      IDIM :HUMEER OF GRAPHS
   *
          ****
    DIMENSION: X(7,60);Y(7,60);U(111);V(56);D(12);E(12);IN(7);
    CHARFCIER *1: A(50/111)/F(111)*1
    REAL MINI, MINI, MAX, MAX1, INCX, INCY
    DO 5 J=1/50
    DO 5 J=1,111
    *=(L\I)A
```

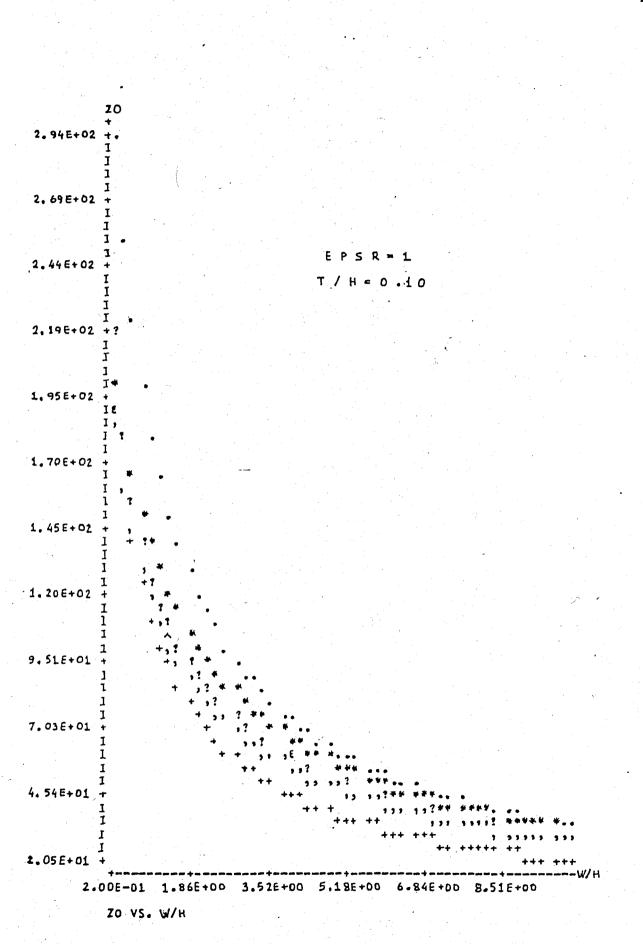
```
5
   CURTINUE
   1F(1x, UT_111_CK, 1x, L1, 2) IX=111
   1F(1),G1_50_08_11_LT_2) IY=50
   IFCNLARG. 1. GRANDLEW. 2) THEN
   DC 11 H=1,101+
   DC 10 1=1/1N(P)
   IF(X(4,I),HF_C) THER
   X (11,1)= AL CU1U (X (11,1))
   ENDIE
10 CONTINUE
   Chu 1F
   IFCKLULD_1_OK.HL_EG_3) THER
   DC 15 H=1,1013
   00 15 1=1/1h(H)
   IF(Y(*,I),NC_C) THER
   Y(11,1)=ALOC14(Y(1,1))
   END IF
15 CONTINUE
   END 1.F
   NO 26 1=1/1X
   F(L)=+--+
23 CONT-1KUE
   03 25 1=1/1X/10
   F(I)=++
25 CONTINUE
   月14キメ(トライ)
   34x=7(1/1)
   NIH1=Y(1,1)
   E(x_1 = y_1(1, 1))
   DC 35 F=1,101*
DO 36 1=1,18(*)
   IF(X(H,I)_GT_MAX) HAX=X(H,I)
   IE(x(H))_LT_P1() ((IN=x(H)))
   1F(Y(K/I)_GT_2AX1) #AX1=Y(H/L)
   IF(Y(H,I) LT: 4141) FIM1=Y(H,I)
30 CONTINUE
35 CONTINUE
   INC X= (HAX=+ Th)/(1X-1)
   INCY=(HAX1-HIN1)/(1Y-1)
   11(1)=H1N
   V(1)=HIN1
   00 41 1=1,11-1
   0(1+1)=0(1)+18CA
40 CONTINUE
   00 45 1=1/11-1
   V(1+1)=V(I)+IACY
45 CONTINUE
   00 65 K=1,101H
   DO 60 1=1/16(P)
   11=1
   DIFF=ABS(x(H,I)-U(1))
   DC 56 J=1,1X--1
   IF(AES(X(H, J)-U(J+1))_LT_D1FF) THEN
   DIFFEAUS(x(4,1) \rightarrow u(1+1)).
   141=J+1
   LND IF
50 CONTINUE
   L=1
```

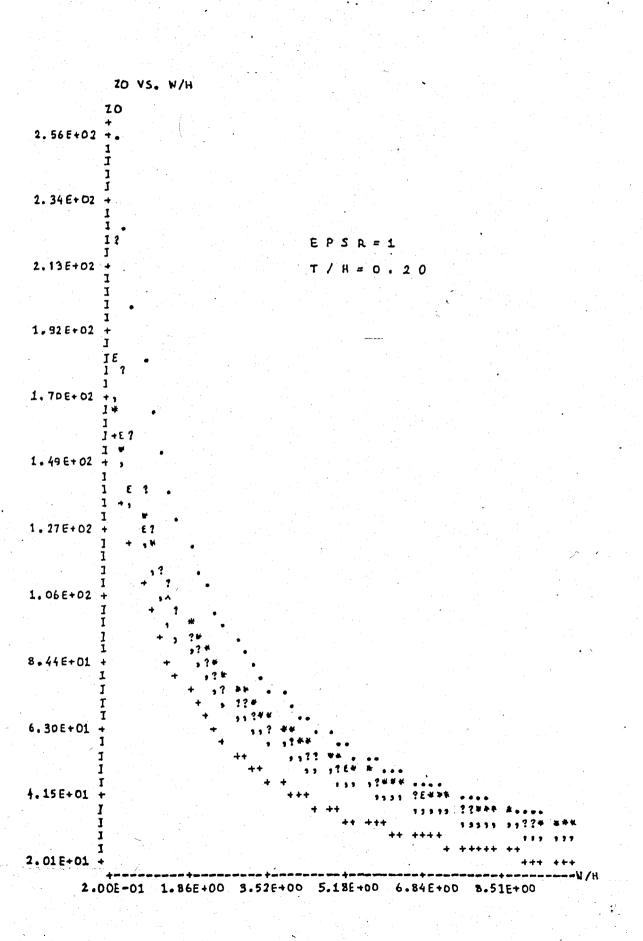
DIFF1=K35(Y(1:,1)-1(1)) 00 55 J=1/1Y++ F IF(ALS(Y(H, I)-V(J+1))_LT_DIFF1) THEN. DIFF1=ABS(Y(H))-V(J+1))-1.=1+1 END IF 55 CONTINUE 1F(/_Eu_1) &(L/41)=*** 1F(H, E4,2) A(L/H1)=1.1 IF(#_F4.3) A(L/41)=*** 1 F (H, EU, 4) A (L/ 41) = "L" IF(P, F4,5) A(L,41)=*8* IF(#_Eu_0) A(L/41)=*?* IF(+,Eu.7) X(L/41)=*/* CONTINUE 65 CCHTINUE 12=0 L3=0 DO 76 1=1,14,5 L2=L2+1 IF(NL.LU.1. OR .HL.EU.2) D(L2)=10**V(I) IFCNLANE, 1. AND. HLANE, 30 D(L2) = V(1) 7.J CC (T160E 00 75 1=1,1x,10 L3=L3+1 IF(NLLE4.1.CK_NLLE4.2) ((L3)=10**U(I) IF(KL_KC_1.4NC_NL_NF_2) E(L3)=U(1) 75 CONTINUE IF(NL_LG. 1. CR. mL_EG. 2) THEN 00 80 N=12101H 00 8[]=1,1N(F) x(4,1)=10**x(*,T) 35 . CONTINUS END IF IF(NELEGAT. OR JAL. EGAS) THEN DC 25 F=1,1013 DC 85 1=1,1N(*) Y(4,1)=1u**Y(8,1) 65 CONTINUE END IF K7=((IY-1)/5)+++ 1P = (1x - 1)/1(+1)PRINT 95 00 SE I=1 Y, 1, -1 IF(I, E4.K7) THLN K.7=K7-5 L=1/5+1 PRINT 100, D(L), (A(I),), J=1, IX) 60 TC 90 END IF PRINT 105, (4(1, J), J=1, IX) 9J CONTINUE PRINT ATU/(F(T)/I=1/1X) PRINT 115/(E(1)/1=1/1P) RETURN 95 ECREAT(1812/) 100 FORMAT(3x,1PL10.2,1X, + 1,11141) ECR#AT(14 XA*1 * A11 1A1) 1.05 110 FORPAT (15 X2 11 14 12 /) FCRMAT(11X/11(1PE9,2/1X)/1PE9.2//) 115 CND

OUTPUTS FOR 6.2

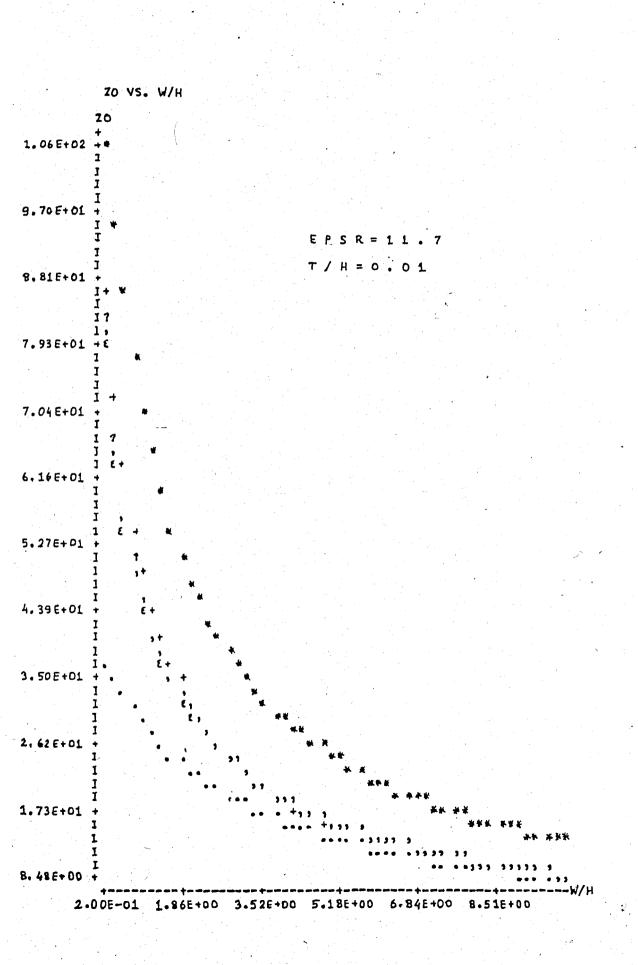


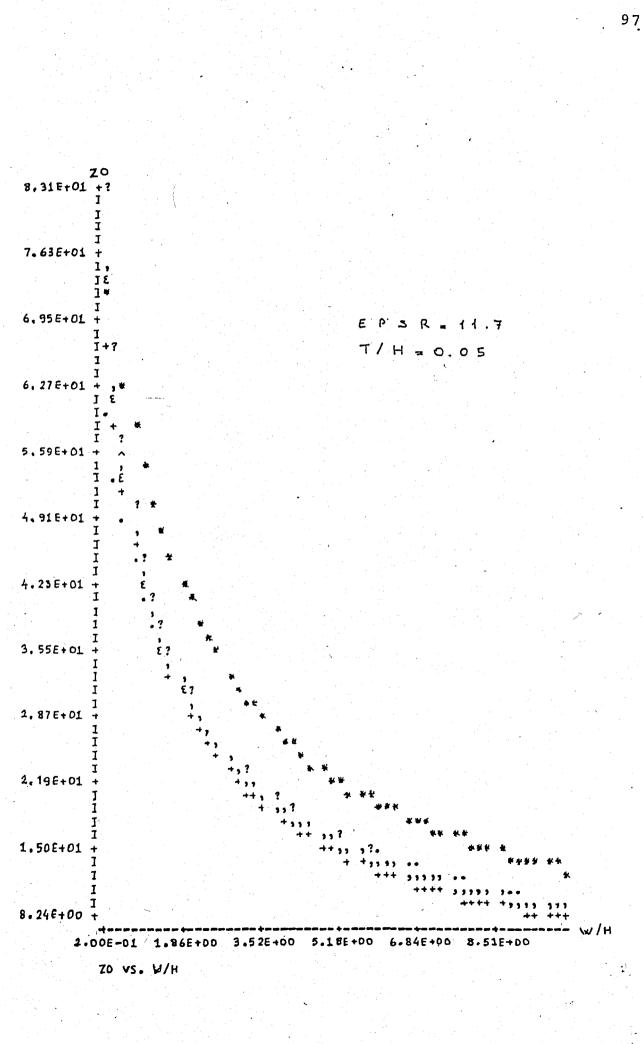


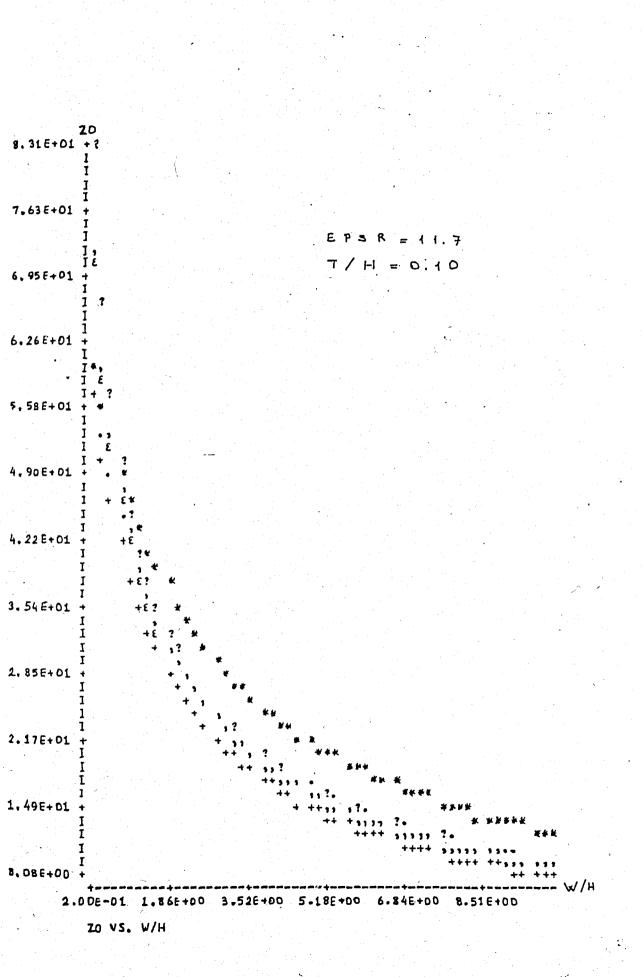


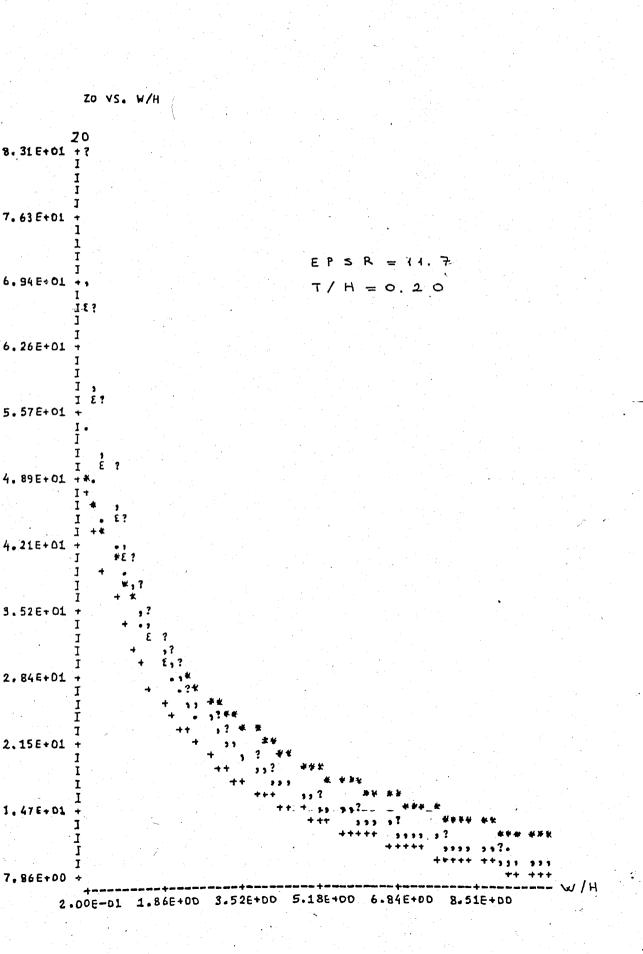


.









VII. CONCLUSION

Microstrip transmission line has in the last few years become very popular in computer and microwave integrated circuit design as can be judged from the large number of papers published on microstrip and microstrip networks. But there is no comprehensive description available at one place. In particular the design information is not readily available. In this study, a detailed account of this line is presented. Section 4.5 on design considerations can be used directly for the design of microstrip line without going into details of analysis. A computer program is also presented in Chapter VI for CAD.

The accuracy needed in equations for microstrip impedance and effective dielectric constant should be set in accordance with typical variations in substrate parameters and manufacturing tolerances, and 1 % as a maximum relative error seems to be a reasonable goal for both. Most of the equations given in section 4.5.1 (except the equations given in f) do not have that accuracy as can be seen from the tables prepared to compare the typical results with the available numerical and experimental results.

From these tables, it is seen that considerable error can arise in the direct application of Eq. 4.20 given in the line-capacitance computation method. Here, one major source of error arises from the use of the relative dielectric permittivity. By considering this point, the method given in b has taken the relative dielectric permittivity in the straight-line approximation neglecting the dependence on microstrip geometry. It has also obtained the constant A_1 , associated with the fringing capacitance as a function of the strip thickness t and the dielectric height h. Similarly A2, associated with the upper-plate capacitance has been obtained as a function of the dielectric height h, the strip conductor width w and the effective dielectric permittivity, ε_{eff} . But there is no physical significance to believe that the constants A1 and A2 depend on microstrip parameters while these parameters have already been accounted for in the capacitance calculations. Also, since the microwave energy propagates both in the dielectric substrate below the strip and in the air region above, the effective dielectric permittivity should be considered as a function of microstrip geometry.

The numerical methods predict a decrease with increase in strip thickness, but the above method (given in c) shows it otherwise i.e. ε_{eff} increases with t/h. (See Table 4.10).

This is ofcourse not acceptable since the fraction of total energy propagating in air increases with strip thickness, there by decreasing the effective dielectric constant. It can be said here that the large amount of error in the results of methods given in b and c appear to be due to the questionable basis for curve fitting. They have tried to fit the experimental results of Kaupp (19) using the equations given in line-capacitance computation method. But these equations have a relative error as large as ±27.6 percent.

Just like the above situation occurred in the methods given in b and c, the formulas for Z_0 and ε_{eff} are obtained by curve fitting the numerical results of Yamashita and Mittra (6) in the method given in e. But these formulas have also an error as large as 12 percent.

In f, new equations intending to have 1 % maximum relative error for both characteristic impedance and effective dielectric permittivity are given first for zero thickness microstrip. Next, since the microstrip is three dimensional and so the strip conductor thickness must be considered, these equations are modified to include strip thickness. A summary of typical results is given in Tables 4.8, 4.9 and 4.10. A comparison of these results with available experimental and numerical results has shown that the results for Z_0 and ε_{eff} given here are correct to within 2 percent for the following set, of parameters : $0 \le t/h \le 0.350$; 0.1 $\le w/h \le 10$ and $\varepsilon_r \le 11.7$.

These simple and most accurate closed form expressions are employed to calculate microstrip characteristics. The results find wide applications in thick microstrips (0.05 \leq t/h \leq 0.2) used in computers and in thin microstrips (0.01 \leq t/h \leq 0.05) used in MIC's.

APPENDIX A

DATA ON COMMONLY USED SUBSTRATES FOR MICROSTRIP (24)

ΤΥΡΕ	EPSE	TEMP. RANGE (°C)	LOSS FAC. (X-BAND)	DIE. STR. (KV/mm)	THER. CON. K[W/N°C]	RELATIVE PRICE
REXOLENE S	2.32	(-60)-(+70)	0.0005	19.7	0.40	1
REXOLITE 1422	2.53	(-60)-(+100)	0.0005	19.7	0.15	3
REXOLITE 2200	2.62	l-75)-(+190)	0.0010	19.7	0.20	2.
POLYPNENYL Oxide	2,55	(-60)-(+260)	0.0016	19.7	0.20	4
3M, K60 98 Cucl D	2,50	(-60)-(+260)	0,0015	31.5	0.10	5
RI/DURDID 5880	2.35	(-60)-(+260)	0.0010	11.8	0.25	10
FUSED SILICA	3.92	NO PRACTICAL LINITATION	0.0001	15.7	1.40	3
BERYLLIA	6.80	1F	0.0003	15.7	230.	8
SAPPHIRE	9.3-11.7	b)	0.0004	19.7	40.0	6
ALUNINA	9,6-9.9	11	0.0004	19.7	35.0	1

APPENDIX A (CONTINUED)

1997) 1997 - 1997 1997 - 1997	
ТҮРЕ	ADVANTAGES
	DISADVANTAGES
REXOLENE S	LOW LOSSES & INEXPENSIVE
	VERY POOR HECHANICAL QUALITIES
REXOLITE	VERY GOOD ELECTRICAL QUALITIES
1422	POOR HECHANICAL QUALITIES
REXOLITE	FAIR ELECTRICAL & HECHANICAL QUALITIES
2200	MODERATE PEEL STRENGTH
POLYPNENY	FAIR ELECTRICAL QUALITIES
OXIDE	POOR HECHANICAL QUALITIES AT THIS PRICE
3N 1 K60 98	VERY GOOD MECHANICAL QUALITIES
54100 54	TEMPERATURE DEPENDENT ELECTRICAL QUALITIES
RI/DUROID	EXCELLENT ELECTRICAL & NECHANICAL QUALITIES
KI/DDR01D	EXPENSIVE
FUSED	LOW EPSR (ADVENTAGEOUS AT HIGH FREQ., X-BAND & ABOVE)
SILICA	
00000	HIGH THERNAL CONDUCTIVITY
BERYLLIA	EXPENSIVE. BERYLLIA DUST IS DANGEROUS, ESPECIALLY IN NOIST ATHOSPHERES AT HIGH TEMPERATURES
5.000	VERY GOOD SURFACE FINISH
SAPPHLRE	EXPENSIVE & ANISOTROPIC
	INEXPENSIVE
ALUMINA	VERY POOR HACHINABILITY

APPENDIX - B

DESIGN OF MICROSTRIP LINES BY USING THETA FUNCTIONS

<u>STEP 1</u>: For a given characteristic impedance Z_0^a , $\frac{K'}{K}$ is calculated from Equation (3.6).

Assume $Z_0^a = 126.95$ ohm. Then by using $Z_0^a = 60_{\Pi K}$ $\kappa = \frac{K'}{\kappa} = 0.673532$.

<u>STEP 2</u> : Modulus m for elliptic functions is found by looking up tables for $\frac{K'}{K}$.

Modulus m is found as = 0.86 from tables (36).

STEP 3 : E, K and K' are found using this value of m.

E = 1.136K = 2.42093K' = 1.63058

<u>STEP 4</u>: The solution of equation $dn^2(2K\S) = \frac{E}{K}$ gives the value of §.

$$dn^2(2KS) = \frac{E}{K} = \frac{1.136}{2.42093} = 0.46924$$

$$2K$$
 = arc dn($\frac{E}{K}$) = 1.02806

$$\$ = \frac{1.02806}{2x2.42093} = 0.212328$$

<u>STEP 5</u>: For known and $\kappa = \frac{K'}{K} = 0.673532$, $\frac{w}{h}$ for the microstrip is calculated from equations (3.4) and (3.7).

$$\frac{\partial}{\partial s} \ln \left[Q_4(s,\kappa) \right] = 4 \Pi \sum_{n=1}^{\infty} \frac{\exp(-n \Pi \kappa)}{1 - \exp(-2n \Pi \kappa)} \operatorname{Sin}(2n \Pi s)$$

For the first 10 terms, this equation equals to

$$\frac{\partial}{\partial s} \ln \left[Q_4(s, \kappa) \right] = 4 \Pi \times (0.124095) = 1.55942$$

From equation (3.4)

$$\frac{w}{h} = \frac{2}{\Pi} \frac{\partial}{\partial S} \ln \left[Q_4(S,\kappa) \right] = \frac{2}{\Pi} \times (1.55942)$$

 $\frac{w}{h} = 0.99276$

BIBLIOGRAPHY

- Schneider, M.V., "Microstrip Lines for Microwave Integrated Circuits", <u>Bell System Tech. Journal</u>, Vol.48, No.5, pp. 1421-1444, May-June 1969.
- Wheeler, H.A., "Transmission-Line Properties of Parallel Wide Strips by a Conformal Mapping Approximation", <u>IEEE</u> <u>Trans. Microwave Theory Tech</u>., Vol. MTT-12, pp. 280-289, Aug. 1964.
- 3. Wheeler, H.A., "Transmission-Line Properties of Parallel Strips Separated by a Dielectric Sheet", <u>IEEE Trans.</u> <u>Microwave Theory Tech.</u>, Vol. MTT-13, pp. 172-185, March 1965.
- 4. Sobol, H., "Application of Integrated Circuit Technology to Microwave Frequencies", Proc. IEEE, Vol. 59, pp. 1200-1211, 1971.
- 5. Stinehelfer, H.E., "An Accurate Calculation of Uniform Microstrip Transmission Lines", <u>IEEE Trans. Microwave</u> Theory Tech., Vol. MTT-16, pp. 439-444, July 1968.
- 6. Yamashita, E. and Mittra, R., "Variational Method for the Analysis of Microstrip Lines", <u>IEEE Trans. Microwave</u> Theory Tech., Vol. MTT-16, pp. 251-256, April 1968.

7. Yamashita, E., "Variational Method for the Analysis of Microstrip-Like Transmission Lines", <u>IEEE Trans. Microwave</u> <u>Theory Tech.</u>, Vol. MTT-16, pp. 529-535, Aug. 1968.

- U -

- 8. W. J. Chudobiak, and Jain O.P., "Dispersion in Microstrip", <u>IEEE Trans. Microwave Theory Tech.</u>, Vol. MTT-19, pp. 783-784, September 1971.
- 9. Getsinger, W.J., "Microstrip Dispersion Model", <u>IEEE</u> <u>Trans. Microwave Theory Tech.</u>, Vol. MTT-21, pp. 34-39, 1973.
- 10. Kompa, G. and R. Mehran, "Planar Waveguide Model for Calculating Microstrip Components", <u>Electron. Lett</u>., Vol. 11, pp. 459-460, 1975.
- 11. Pucel, R.A., "Losses in Microstrip", <u>IEEE Trans. Microwave</u> Theory Tech., Vol. MTT-16, pp. 342-350, June 1968.
- 12. Wheeler, H.A., "Formulas for the Skin Effect," <u>Proc. IRE</u>, Vol. 30, pp. 412-424, 1942.
- 13. Schneider, M.V., "Dielectric Loss in Integrated Microwave Circuits", <u>Bell System Tech. Jounal</u>, Vol. 48, pp. 2325-2332, Sept. 1969.

- 14. Simpson, T.L., and B. Tseng, "Dielectric Loss in Microstrip Lines", <u>IEEE Trans. Microwave Theory Tech</u>., Vol. MTT-24, pp. 106-108, Feb. 1976.
- 15. Farrar, A., and A.T., Adams, "Characteristic Impedance of Microstrip by the Method of Moments", <u>IEEE Trans.</u> Microwave Theory Tech., Vol. MTT-18, pp. 65-66, Jan. 1970.
- 16. Schwarzmann, A., "Microstrip Plus Equations Add up to Fast Designs", <u>Electronics</u>, Vol. 40, pp. 109-112, Oct. 1967.
- 17. John, S., and P., Arlett, "Simple Method for the Calculation of the Characteristic Impedance of Microstrip", <u>Electron. Lett.</u>, pp. 188-190, May 1974.
- 18. Kumar, A., et al., "A Method for the Calculation of the Characteristic Impedance of Microstrip", <u>Int. Journal</u> of Electronics, Vol. 40, pp. 45-47, Jan. 1976.
- 19. Kaupp, H.R., "Characteristics of Microstrip Transmission Lines, "<u>IEEE Trans. Microwave Theory Tech</u>., Vol. EC-16, pp. 185-193, 1967.
- 20. Ross, R.F.G., and M.J., Howes, "Simple Formulas for Microstrip Lines", <u>Electron. Lett.</u>, p. 410, Aug. 5, 1976.

- 21. Bryant, T.G., and J.A., Weiss, "Parameters of Microstrip Transmission Lines and of Coupled Pairs of Lines, "<u>IEEE</u> <u>Trans. Microwave Theory Tech.</u>, Vol. MTT-16, pp. 1021-1027, Dec. 1968.
- 22. Hammerstad, E.O., "Equations for Microstrip Circuit Design, "Proc. European Microwave Confo, pp. 268-272, 1975.
- 23. Bahl, I.J., and R., Garg, "Simple and Accurate Formulas for Microstrip with Finite Strip Thickness", Proc. IEEE, Vol. 65, pp. 1611-1612, 1977.
- 24. Hammerstad, E.O., <u>Microstrip Handbook</u>. Trondheim : ELAB Report, 1975, p. 70.
- 25. Gunston, M.A.R., <u>Microwave Transmission Line Impedance</u> Data. London : Van Nostrand, 1972, pp. 48-49.
- 26. Bahl, I.J., "Easy and Exact Methods for Shielded Microstrip Design, "Microwaves, Vol. 17, pp. 32-37, Dec. 1978.
- 27. Edwards, T.C., and R.P., Owens, "2-18 GHz Dispersion Measurements on 10-100 ohm Microstrip Line on Sapphire," <u>IEEE Trans. Microwave Theory Tech.</u>, Vol. MTT-24, pp. 506-513, 1976.

- 28. Krage, M.K., and G.I., Haddad, "Frequency Dependent Characteristics of Microstrip Transmission Lines", <u>IEEE Trans. Microwave Theory Tech.</u>, Vol. MTT-20, pp. 678-688, Oct. 1972.
- 29. Owens, R.P., "Predicted Frequency Dependence of Microstrip Characteristic Impedance Using the Plonar Waveguide Model", <u>Electron. Lett.</u>, Vol. 12, No. 11, pp. 269-270, May 1976.
- 30. Bianco, B., et. al., "Frequency Dependence of Microstrip Parameters", <u>Alta Frequenta</u>, Vol. 43, pp. 413-416, 1974.
- 31. Knorr, J.B. and Tüfekcioğlu, A., "Spectral Domain Calculation of Microstrip Characteristic Impedance", <u>IEEE</u> <u>Trans. Microwave Theory Tech</u>., Vol. MTT-23, pp. 725-728, Sept. 1975.
- 32. Belohoubek, E., and E.J., Denlinger, "Loss Considerations for Microstrip Resonators", <u>IEEE Trans. Microwave Theory</u> <u>Tech.</u>, Vol. MTT-23, pp. 522-526, 1975.
- 33. Napoli, L.S. and J.J. Hughes, "A Simple Technique for the Accurate Determination of the Microwave Dielectric Constant for Microwave Integrated Circuits", <u>IEEE Trans. Microwave</u> Theory Tech., Vol. MTT-19, pp. 664-665, 1971.
- 34. Howell, J.Q., "A Quick, Accurate Method to Measure the Dielectric Constant of Microwave Integrated Circuit

Substrates", <u>IEEE Trans. Microwave Theory Tech</u>., Vol. MTT-21, pp. 142-143, 1973.

- 35. Pannell, R.M. and Jervis B.W., "Two Simple Methods for the Measurement of the Dielectric Permittivity of Low-Loss Microstrip Substrates", <u>IEEE Trans. Microwave</u> <u>Theory Tech.</u>, Vol. MTT-29, pp. 383-386, 1981.
- 36. Abramowitz, M., and Stegun, I.A., <u>Handbook of Mathematical</u> <u>Functions</u>, National Bureau of Standards, Applied Mathematics Series 55,2nd Printing, pp. 608-609, November 1964.

REFERENCES NOT CITED

- Arditi, M., "Characteristics and Applications of Microstrip for Microwave Wiring", <u>IRE Trans. Microwave Theory</u> <u>Tech.</u>, Vol. MTT-3, pp. 31-56, March 1955.
- Arndt, F. and G. Paul, E., "The Reflection Definition of the Characteristic Impedance of Microstrips", <u>IEEE Trans</u>. <u>Microwave Theory Tech.</u>, Vol. MTT-27, pp. 724-731, Aug. 1979.
- Assadourian, F. and E., Rimai, "Simplified Theory of Microstrip Transmission Systems", <u>Proc. IRE</u>, Vol. 40, pp. 1651-1657, Dec. 1952.
- Atsuki, K. and E., Yamashita, "Analysis of Microstrip-Like Transmission Lines by Non-Uniform Discretization of Integral Equations", <u>IEEE Trans. Microwave Theory</u> Tech., Vol. MTT-24, pp. 195-200.
- Atwater, H.A., "Microstrip Reactive Circuit Elements", <u>IEEE</u> <u>Trans. Microwave Theory Tech.</u>, Vol. MTT-31, pp. 488-491, June 1983.

- Bahl, I.J. and K.C., Gupta, "Average Power Handling Capability of Microstrip Lines", <u>IEE Jour. on Microwaves, Optics</u> <u>and Acoustics</u>, Jan. 1979.
- Belohoubek, E., and E.J., Denlinger, "Loss Considerations for Microstrip Resonators", <u>IEEE Trans. Microwave Theory</u> Tech., Vol. MTT-23, pp. 522-526, July 1975.
- Bhat, B. and S.K., Koul, "Unified Approach to Solue a Class of Strip and Microstrip-Like Transmission Lines", <u>IEEE Trans. Microwave Theory Tech.</u> Vol. MTT-30, pp. 679-686, May 1982.
- Bianco B. et al., "Some Considerations About the Frequency Dependence of Uniform Microstrips," <u>IEEE Trans. Micro-</u> wave Theory Tech., Vol. MTT-26, pp. 182-185, Mar. 1978.
- Black K.G. and T. Higgins, "Rigorous Determination of the Parameters of Microstrip Transmission Lines," <u>IRE</u> <u>Trans. Microwave Theory Tech.</u>, Vol. MTT-3, pp. 93-113, March 1955.
- Bryant T.G. and J.A. Weiss, "Parameters of Microstrip", <u>Elec-</u> <u>tronics Letters</u>, Vol. 5, pp. 517-518, Oct. 1969.
- Bryant T.G. and J.A. Weiss, "MSTRIP (Parameters of Microstrip)", <u>IEEE Trans. Microwave Theory Tech.</u>, Vol. MTT-19, pp. 418, Apr. 1971.

- Callarotti, R.C., "On the Solution of a Microstripline with Two Dielectrics", <u>IEEE Trans. Microwave Theory Tech</u>., Vol. MTT-32, pp. 333-338, April 1984.
- Capelle, A.R., "Fundamental and Higher Order Modes in Open Microstrip Lines", <u>Electronics Letters</u>, Vol. 9, No. 15, pp. 345-346, July 1973.
- Capelle, A.R. and H. Pues, "Approximate Formulas for Frequency Dependence of Microstrip Parameters", <u>Electronics</u> Letters, Vol. 16, No. 23, pp. 870-872, Nov. 1980.
- Carlin, H.J., "A Simplified Circuit Model for Microstrip", <u>IEEE Trans. Microwave Theory Tech</u>., Vol. MTT-21, pp. 589-591, Sept. 1973.
- Caulton, M., J.J. Hughes, and H. Sobol, "Measurement of the Properties of Microstrip Transmission Lines for Microwave Integrated Circuits", <u>RCA Rev.</u>, Vol. 27, pp. 377-391, Sept. 1966.
- Cloves, R.J., S.V. Judd, I. Whiteley, and D.C. Rickard, "An Analytical Method for Calculating Microstrip Transmission Line Parameters", <u>IEEE Trans. Microwave</u> Theory Tech., Vol. MTT-18, pp. 78-88, Feb. 1970.

- Coen, S. and, G.M.L. Gladwell, "A chebyshev Approximation. Methods for Microstrip Problems, "<u>IEEE Trans. Microwave</u> <u>Theory Tech</u>., Vol. MTT-23, pp. 865-870, Nov. 1975.
- Cohn, S.B., "Problems in Strip Transmission Lines", <u>IRE</u> <u>Trans. Microwave Theory Tech</u>., Vol. MTT-3, pp. 119-126, March 1955.
- Cory, H., "Dispersion Characteristics of Microstrip Lines," <u>IEEE Trans. Microwave Theory Tech</u>., Vol. MTT-29, pp. 59-62, Jan. 1981.
- Crampagne, R. and G. Khoo, "Analysis and Synthesis of MIC Transmission Lines", <u>Microwave Journal</u>, pp. 105-106, June 1977.
- Daly, P., "Hybrid Mode Analysis of Microstrip by Finite Element Methods", IEEE Trans. Microwave Theory Tech., Vol. MTT-19, pp. 19-25, Jan.1971.
- Davies, J.B. and D.M. Syahkal, "Accurate Solutions of Mic-Rostrip and Coplanar Structures for Dispersion and for Dielectric and Conductor Losses," <u>IEEE Trans</u>. <u>Microwave Theory Tech</u>., Vol. MTT-27, pp. 694-699, July 1979.

- Denlinger, E.J., "Radiation from Microstrip Resonators", <u>IEEE Trans. Microwave Theory Tech.</u>, Vol. MTT-16, pp. 235-236, Feb. 1969.
- Denlinger, E.J., "A Frequency Dependent Solution for Microstrip Transmission Lines", <u>IEEE Trans. Microwave Theory Tech</u>., Vol. MTT-19, pp. 30-39, Jan. 1971.
- Dukes, J.M.C., "An Investigation into Some Fundamental Properties of Strip Transmission Lines with the Aid of an Electrolytic Tank," <u>Proc. IEE</u>, Vol. 103, Part B, pp. 319-333, May 1956.
- Easter, B., R. Horton and A. Gopinath, "Varration of Microstrip Losses with Thickness of Strip", <u>Electronics Letters</u>, Vol. 7, No. 17, pp. 490-491.
- Easter, B., "The Equivalent Circuit of Some Microstrip Discontinuities," <u>IEEE Trans. Microwave Theory Tech.</u>, Vol. MTT-23, pp. 655-660, 1975.
- Enzelmann, H. and D.D. Griez, "Microstrip-A New Transmission Technique for the Kilomegacycle Range," <u>Proc. IRE</u>, Vol. 40, pp. 1644-1650, Dec. 1952.
- Garg, R., "The Effect of Tolerances on Microstrip Line and Slotline Performance", <u>IEEE Trans. Microwave Theory</u> Tech., Vol. MTT-26, pp. 16-19, 1978.

Getsinger, W.J., "Microstrip Characteristic Impedance", <u>IEEE Trans. Microwave Theory Tech</u>., Vol. MTT-27, pp. 293, Apr. 1979.

- Getsinger, W.J., "Measurement and Modeling of the Apparent Characteristic Impedance of Microstrip", <u>IEE Trans</u>. Microwave Theory Tech., Vol. MTT-31, pp. 624-632, Aug. 1983.
- Gopinath, A., and J.S. Hornsby, "Fourier Analysis of a Dielectric-loaded Waveguide with a Microstrip Line", Electronics Letters, Vol. 5, pp. 265-267, June 1969.
 - Gopinath, A., and R. Norton, "Microstrip Loss Calculations", <u>Electronics Letters</u>, Vol. 6, No.2, pp. 40-41, Jan. 1970.
 - Green, H.E., "The Numerical Solution of Some Important Transmission Line Problems", IEEE Trans. Microwave Theory <u>Tech.</u>, MTT-13, pp. 676-692, Sept. 1965.
- Gunston, M.A.R. and J.R., Weale, "The Transmission Characteristics of Microstrip," <u>The Marconi Review</u>, pp. 226-224, 1969.
- Heuven, J.H.C., "Conduction and Radiation Losses in Microstrip, <u>IEE Trans. Microwave Theory Tech.</u>, Vol. MTT-22, pp. 841-844, 1974.

- Hilberg, W., "From Approximations to Exact Relations for Characteristic Impedances," <u>IEEE Trans. on Microwave</u> <u>Theory Tech.</u>, MTT-17, No. 5, pp. 259-265, May 1969.
- Hughes, J. and L. Napoli, "High Frequency Behaviour of Microstrip Transmission Lines," <u>RCA Rev</u>. Vol. 30, pp. 268-276, June 1969.
- Hyltin, T.M., "Microstrip Transmission on Semiconductor Dielectrics," IEEE Trans. Microwave Theory Tech., Vol. MTT-13, pp. 777-781, Nov. 1965.
- Itoh, T. and R. Mittra, "A New Technique for the Analysis of the Dispersion Characteristics of Microstrip Lines," <u>IEEE Trans. Microwave Theory Tech.</u>, Vol. MTT-19, pp. 47-56, Jan. 1971.
- Itoh, T., "SPectral-Domain Approach for Calculating the Dispersion Characteristics of Microstrip Lines", <u>IEEE Trans. Microwave Theory Tech</u>., Vol. MTT-21, pp. 496-499, July 1973.
- Itoh, T. and R. Mittra, "A Technique for Computing Dispersion Characteristics of Shielded Microstrip Lines," <u>IEEE</u> <u>Trans. Microwave Theory Tech.</u>, Vol. MTT-22, pp. 896-898, Oct. 1974.

- Itoh, T., "Analysis of Microstrip Resonators", <u>IEEE Trans.</u> <u>Microwave Theory Tech.</u>, Vol. MTT-22, No.11, pp. 946-952, Nov. 1974.
- Knorr, J.B. and A. TÜFEKCİOĞLU, "Spectral-Domain Calculation of Microstrip Characteristic Impedance", <u>IEEE Trans.</u> <u>Microwave Theory Tech.</u>, Vol. MTT-23, pp. 725-728, Sept. 1975.
- Kostriza, J.A., "Microstrip Components", Proc. IRE, Vol. 40, pp. 1658-1663, Dec. 1952.
- Kuester, E.F., "Accurate Approximations for a Function Appeari in the Analysis of Microstrip", <u>IEEE Trans. Microwave</u> <u>Theory Tech.</u>, Vol. MTT-32, pp. 131-133, Jan. 1984.
- Levige, W.V., et. al., "New Waveguide Structures for Millimete Wave and Optical Integrated Circuits," <u>IEEE Trans</u>. Microwave Theory Tech., Vol. MTT-23, pp. 655-660, 1975.
- Owens, R.P., "Curvature Effect in Microstrip Ring Resonators," Electron. Lett., Vol. 12, pp. 356-357, 1976.

- Poh., S.Y., "Approximate Formulas for Line Capacitance and Characteristic Impedance of Microstrip Line", <u>IEEE Trans</u>. <u>Microwave Theory Tech</u>., Vol. MTT-29, pp. 135-143, Feb. 1981.
- Richings, J.G., "An Accurate Experimental Method for Determining the Important Properties of Microstrip Transmission Lines," <u>Marconi Review</u>, pp. 210-216, 1974.
- Schneider, M.V., "Microstrip Dispersion", Proc. IEEE, pp. 144-146, Jan. 1972.
- Seckelmann, R., "On the Measurement of Microstrip Properties", Microwave Journal, Vol. 11, pp. 61-64, Jan. 1968.
- Sherbiny, A.M.A., "Hybrid Mode Analysis of Microstrip Lines on Anisotropic Substrates", <u>IEEE Trans. Microwave</u> Theory Tech., Vol. MTT-29, pp. 1261-1266, Dec. 1981.
- Syahkal, D.M., "An Accurate Determination of Dielectric Loss Effect in Monolithic Microwave Integreted Circuits Including Microstrip and Coupled Microstrip Lines", <u>IEEE Trans. Microwave Theory Tech</u>., Vol. MTT-31, pp. 950-954, Nov. 1983.
- Szentkuti, B.T., "Simple Analysis of Anisotropic Microstrip Lines by a Transform Method," <u>Electron. Lett</u>., Vol. 12, pp. 672-673, 1976.

Troughton, P., "Measurement Techniques in Microstrip," Electron. Lett., Vol. 5, pp. 25-26, Jan. 1969.

- Wu, T.T., "Theory of the Microstrip", <u>J. Appl. Phys.</u>, Vol. 28 pp. 299, 1957.
- Yamashita, E., "An Approximate Dispersion Formula of Microstrip Lines for Computer-Aided Design of Microwave Integrated Circuits", <u>IEEE Trans. on Microwave Theory and Tech</u>., Vol. MTT-27, pp. 1036-1038, Dec. 1979.